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(12) **United States Patent**
Silverbrook

(10) **Patent No.:** **US 7,066,575 B2**
(45) **Date of Patent:** **Jun. 27, 2006**

(54) **MICRO-ELECTROMECHANICAL FLUID
EJECTION DEVICE HAVING A
BUCKLE-RESISTANT ACTUATOR**

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(Continued)

(75) Inventor: **Kia Silverbrook**, Balmain (AU)

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(73) Assignee: **Silverbrook Research Pty Ltd**,
Balmain (AU)

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(*) Notice: Subject to any disclaimer, the term of this
patent is extended or adjusted under 35
U.S.C. 154(b) by 0 days.

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(21) Appl. No.: **10/968,922**

Abstract JP 2265751 Oct. 30, 1990 App No. 6486202
(Matsushita Electric Ind Co Ltd).

(Continued)

(22) Filed: **Oct. 21, 2004**

Primary Examiner—Stephen Meier

Assistant Examiner—An H. Do

(65) **Prior Publication Data**

US 2005/0057610 A1 Mar. 17, 2005

(57) **ABSTRACT**

Related U.S. Application Data

(63) Continuation of application No. 10/728,887, filed on
Dec. 8, 2003, now Pat. No. 6,824,252, which is a
continuation of application No. 10/309,080, filed on
Dec. 4, 2002, now Pat. No. 6,682,176, which is a
continuation-in-part of application No. 09/113,122,
filed on Jul. 10, 1998, now Pat. No. 6,557,977.

A micro-electromechanical fluid ejection device includes a substrate that defines a fluid inlet channel and incorporates a wafer and CMOS layers positioned on the wafer. A nozzle chamber structure is positioned on the substrate to define a nozzle chamber in fluid communication with the fluid inlet channel and a fluid ejection port in fluid communication with the nozzle chamber. The nozzle chamber structure incorporates a fluid ejecting member that is displaceable with respect to the substrate to act on fluid in the nozzle chamber to eject the fluid from the fluid ejection port. An elongate actuator arm is connected at one end to the substrate and at an opposite end to the fluid ejecting member. The arm has an active beam assembly and a passive beam assembly spaced from and parallel to the active beam assembly. The beam assemblies are mechanically connected, but electrically isolated from each other. The active beam assembly defines an electrical heating circuit connected to the CMOS layers and capable of thermal expansion so that the arm experiences differential thermal expansion to be displaced with respect to the substrate thus displacing the fluid ejecting member. A spacing between the active beam assembly and the passive beam assembly is between one percent and twenty percent of a length of the actuator arm.

(30) **Foreign Application Priority Data**

Jul. 15, 1997 (AU) PO7991
Jul. 15, 1997 (AU) PO7991
Jul. 15, 1997 (AU) PO8004

(51) **Int. Cl.**
B41J 2/04 (2006.01)
B41J 2/05 (2006.01)

(52) **U.S. Cl.** **347/54; 347/65**

(58) **Field of Classification Search** **347/54,**
347/56, 65

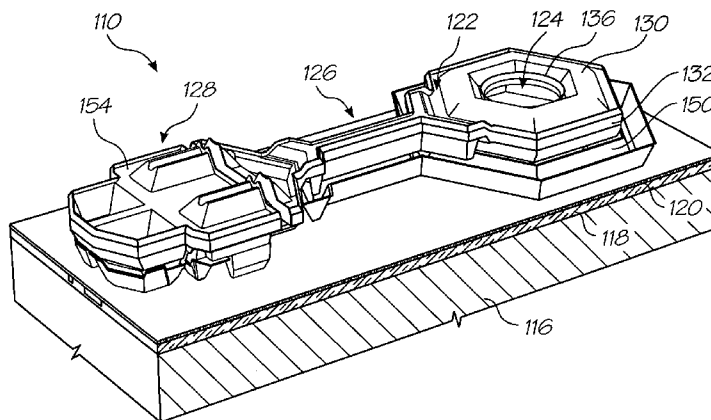
See application file for complete search history.

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7 Claims, 42 Drawing Sheets



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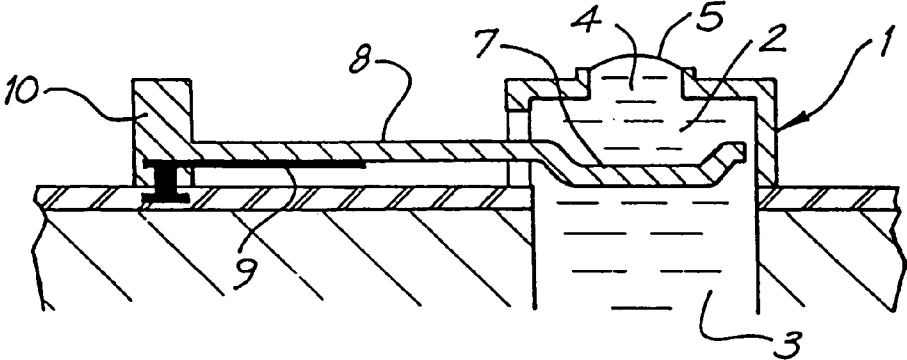


FIG. 1

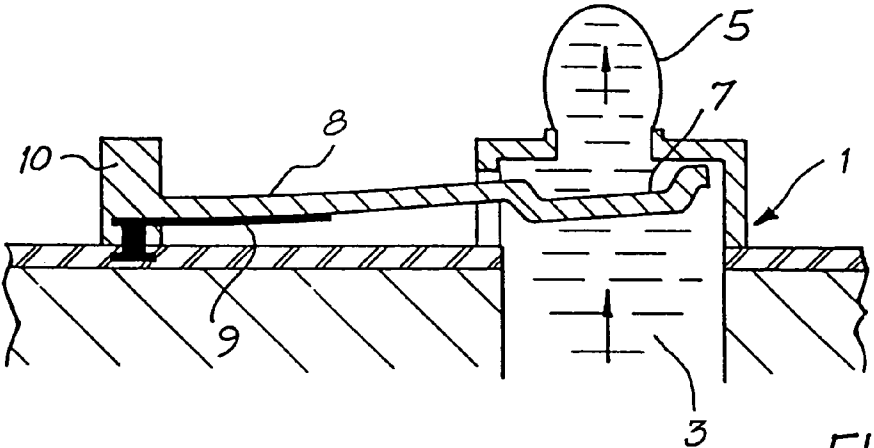


FIG. 2

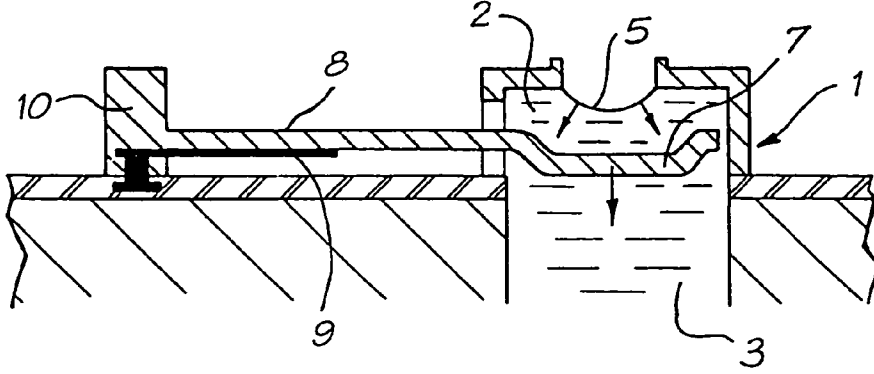
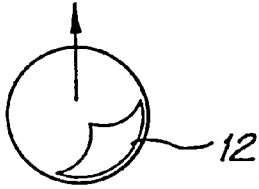
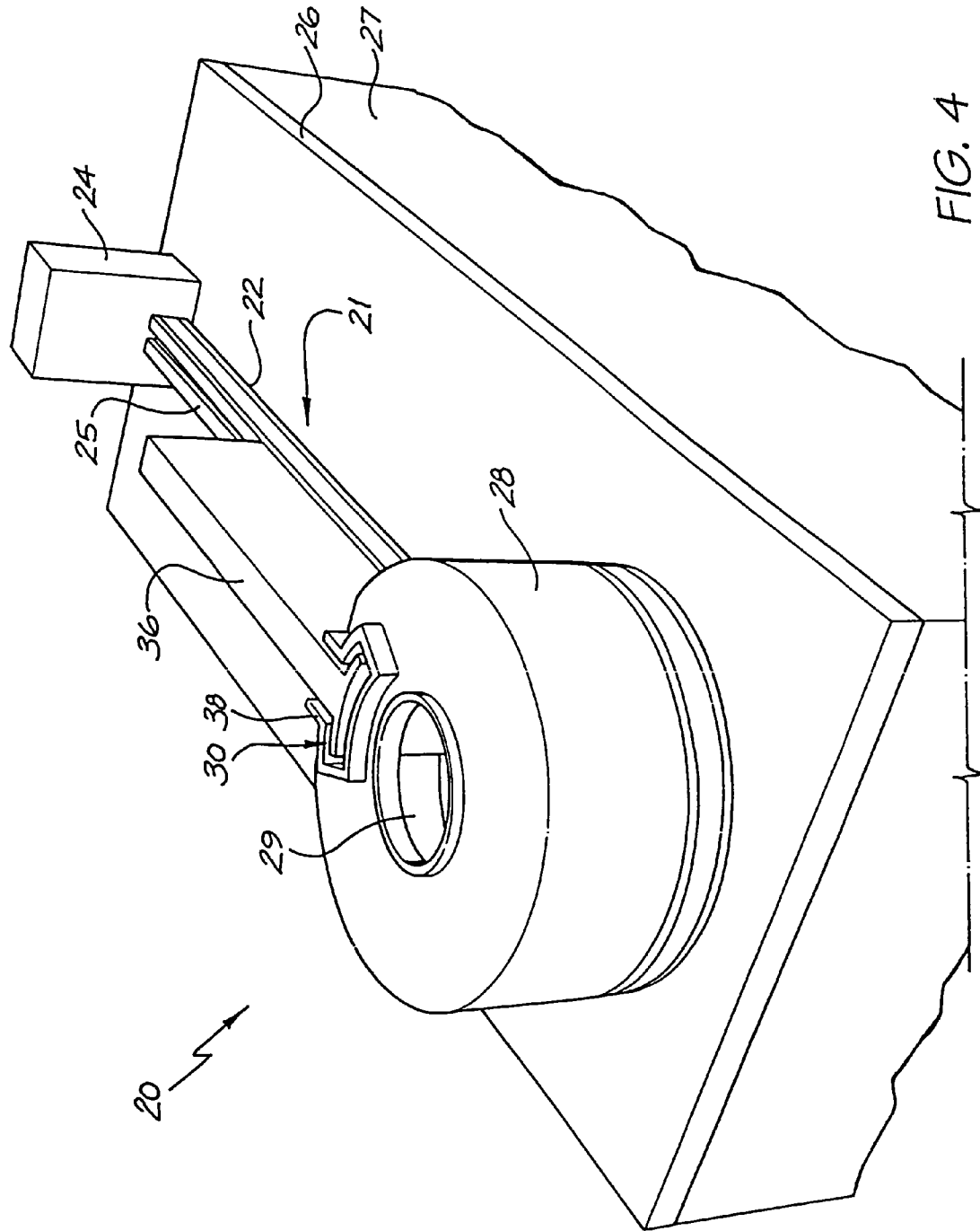
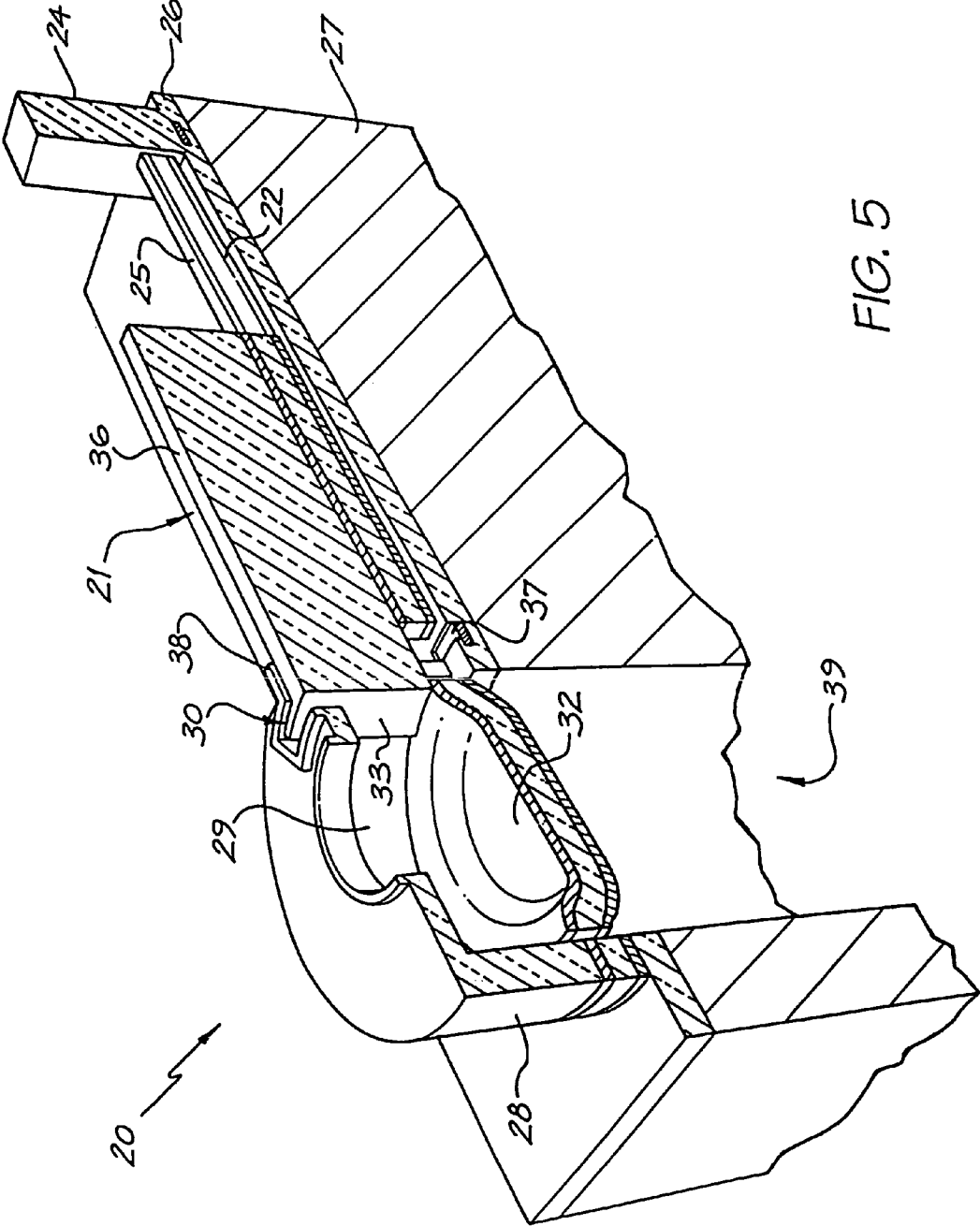


FIG. 3





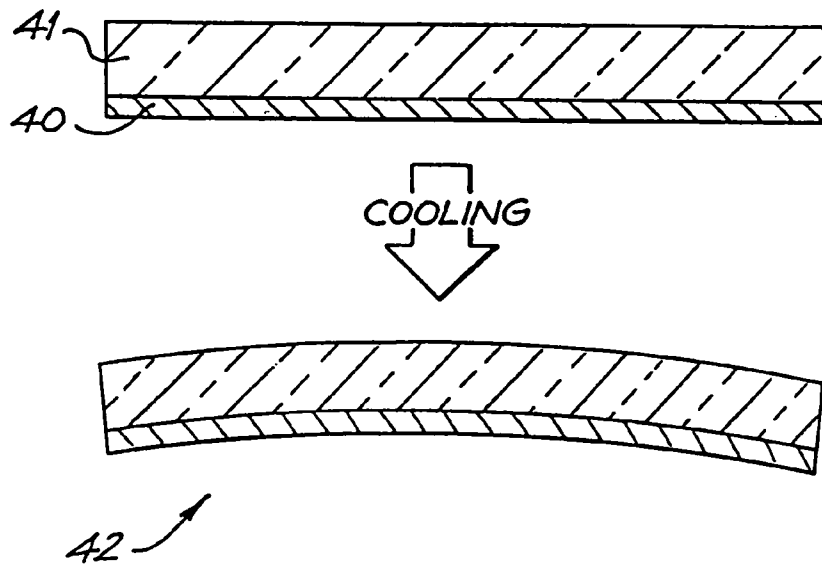


FIG. 6

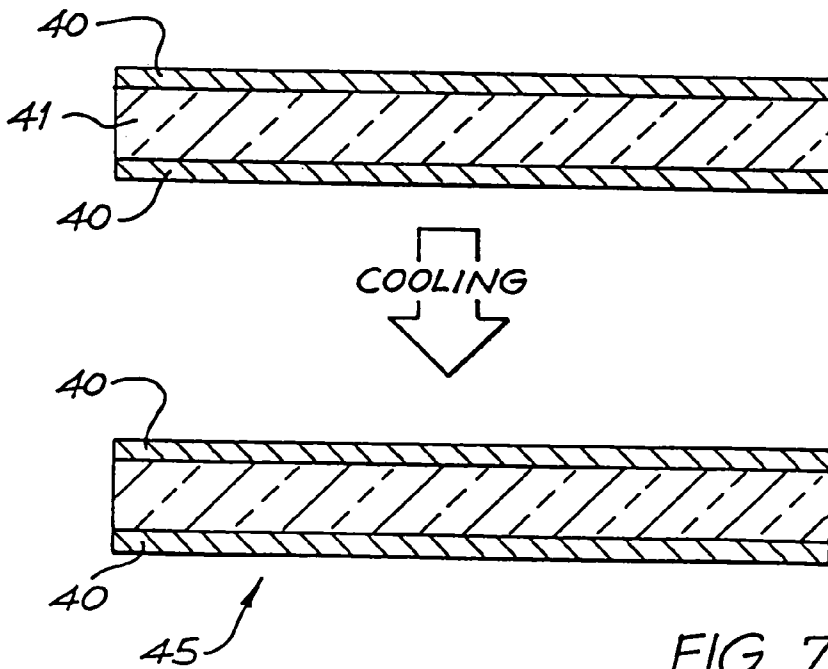


FIG. 7

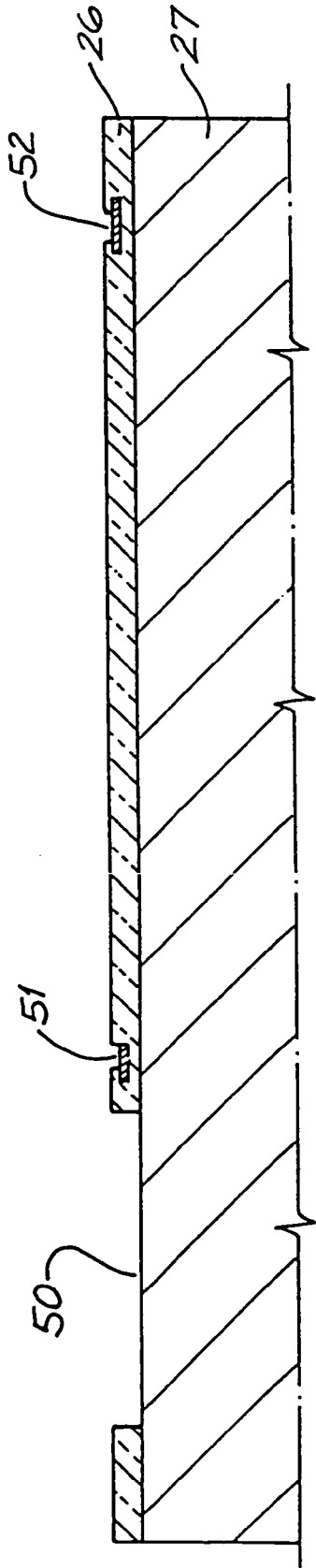


FIG. 8

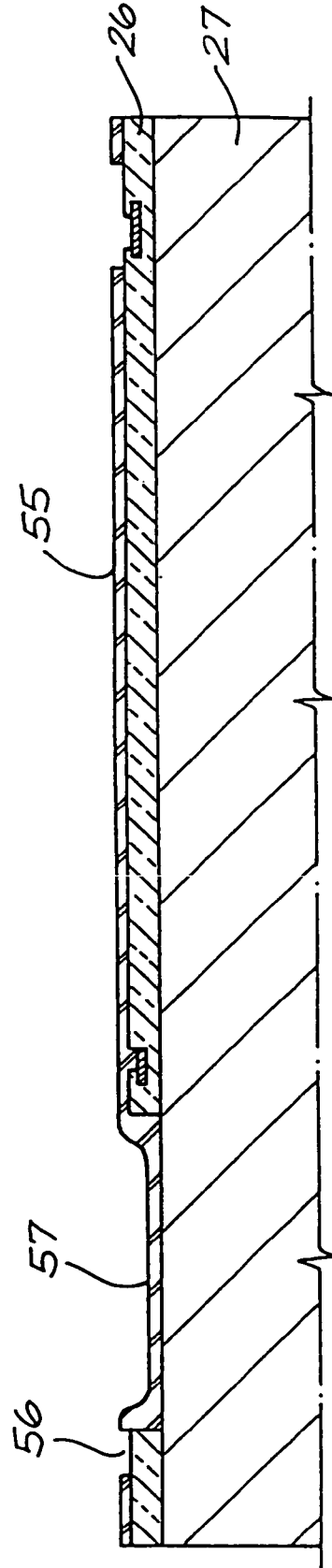


FIG. 9

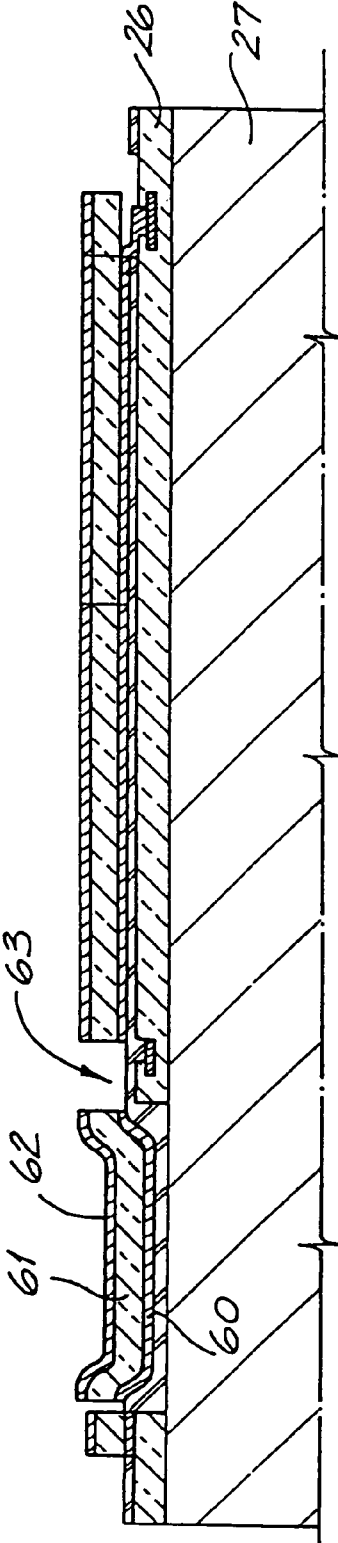


FIG. 10

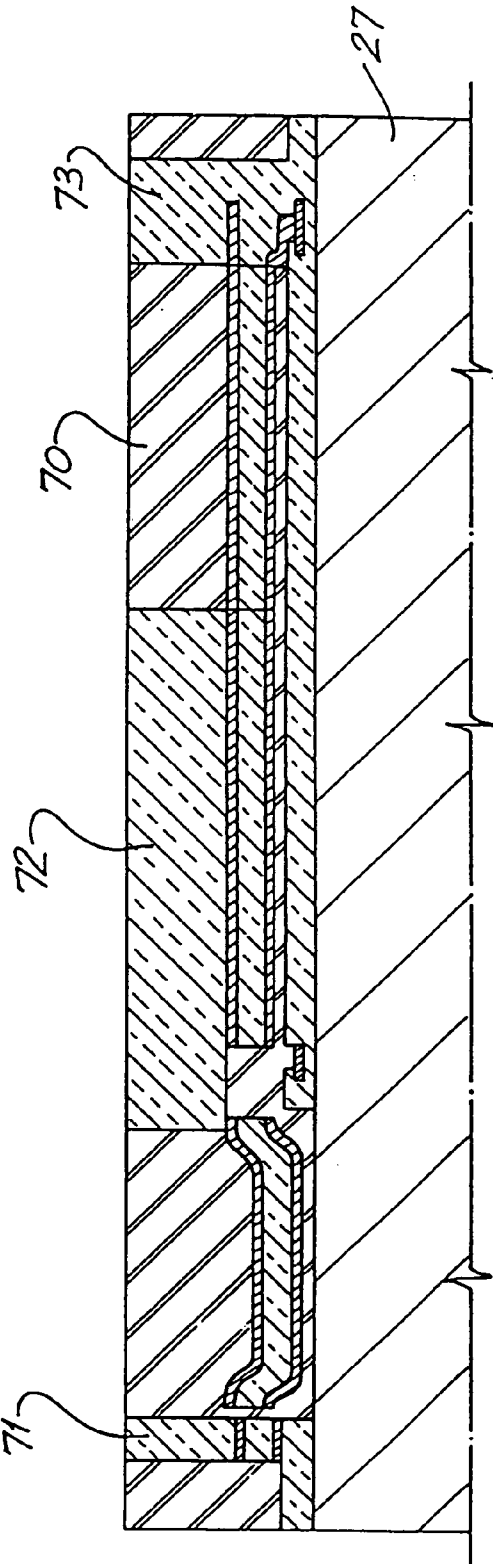


FIG. 11

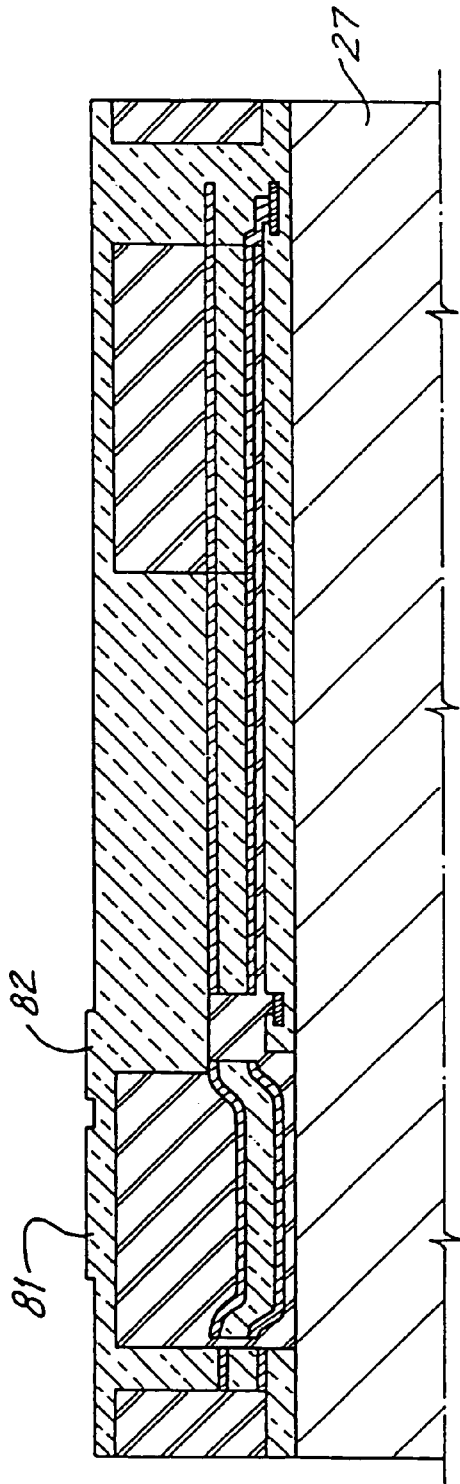


FIG. 12

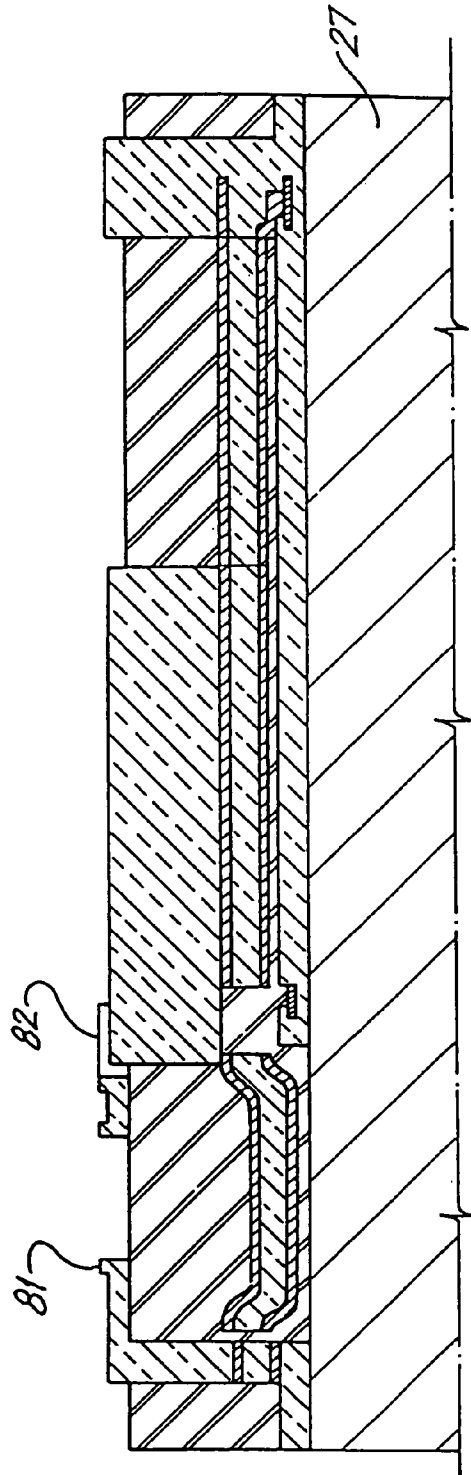


FIG. 13

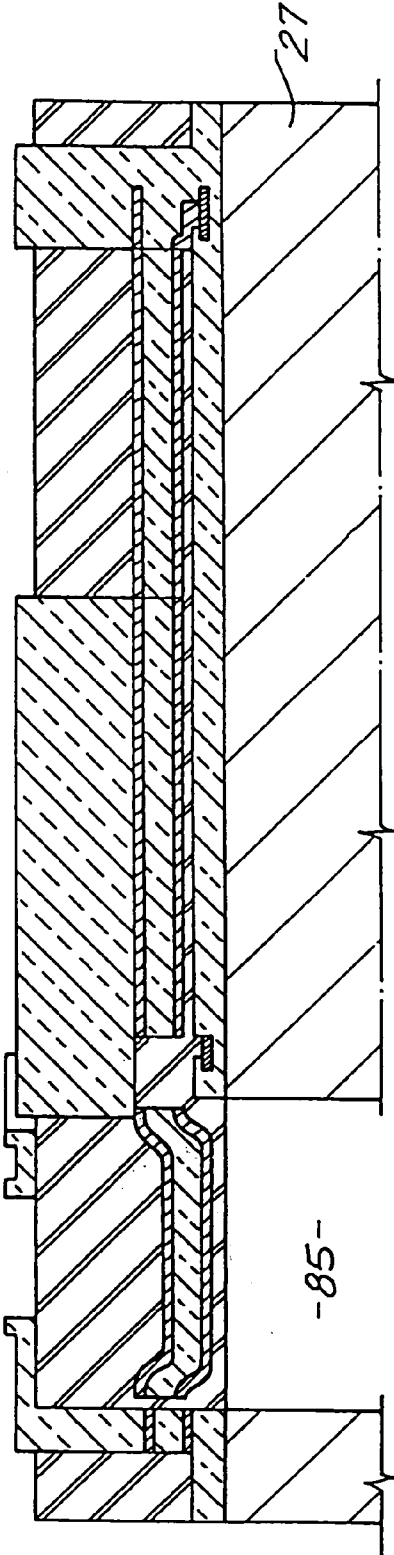


FIG. 14

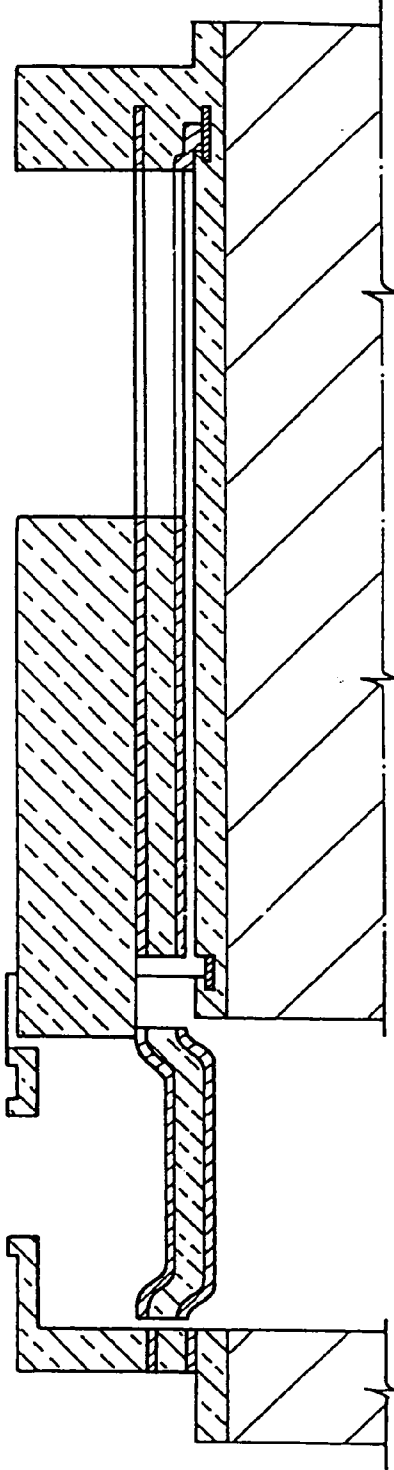


FIG. 15

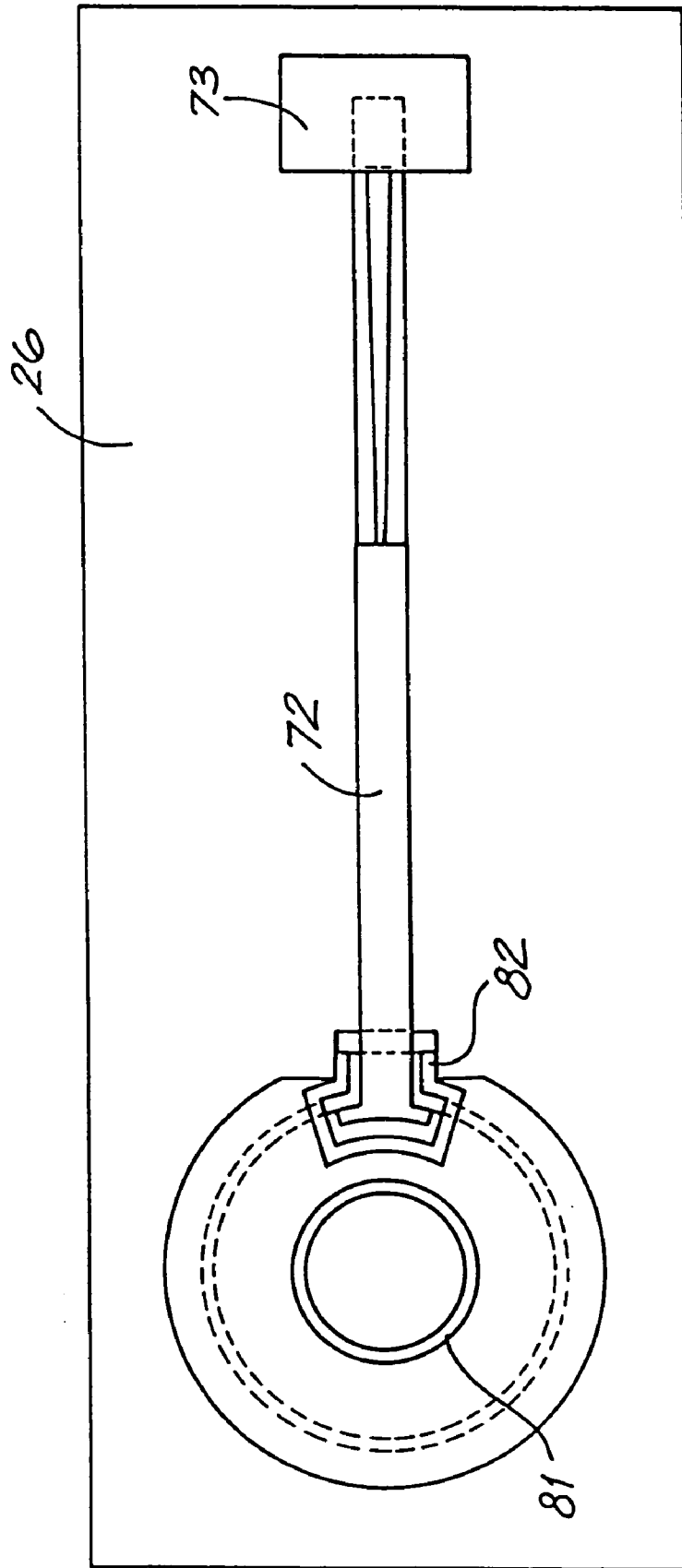


FIG. 16

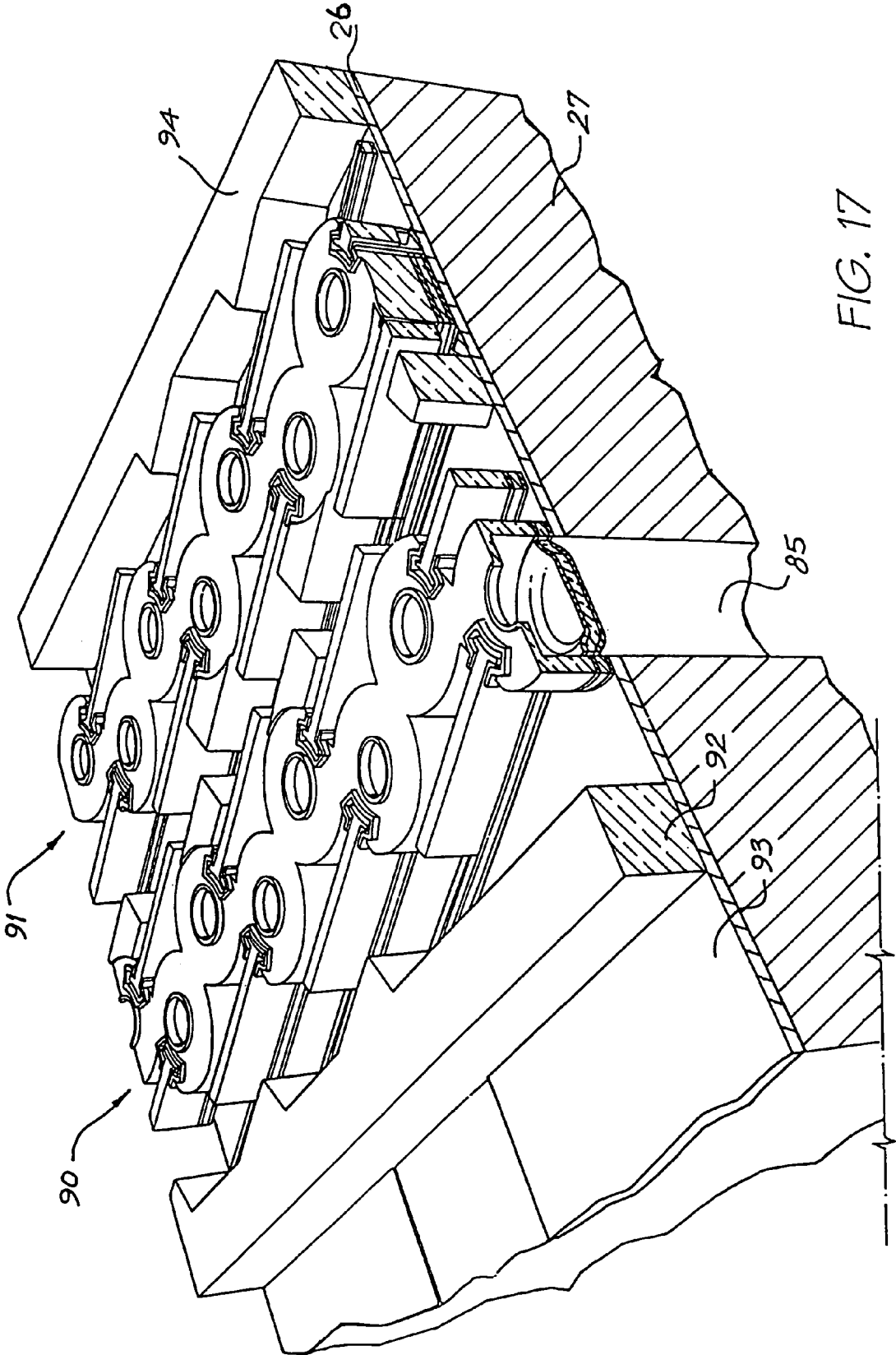


FIG. 17

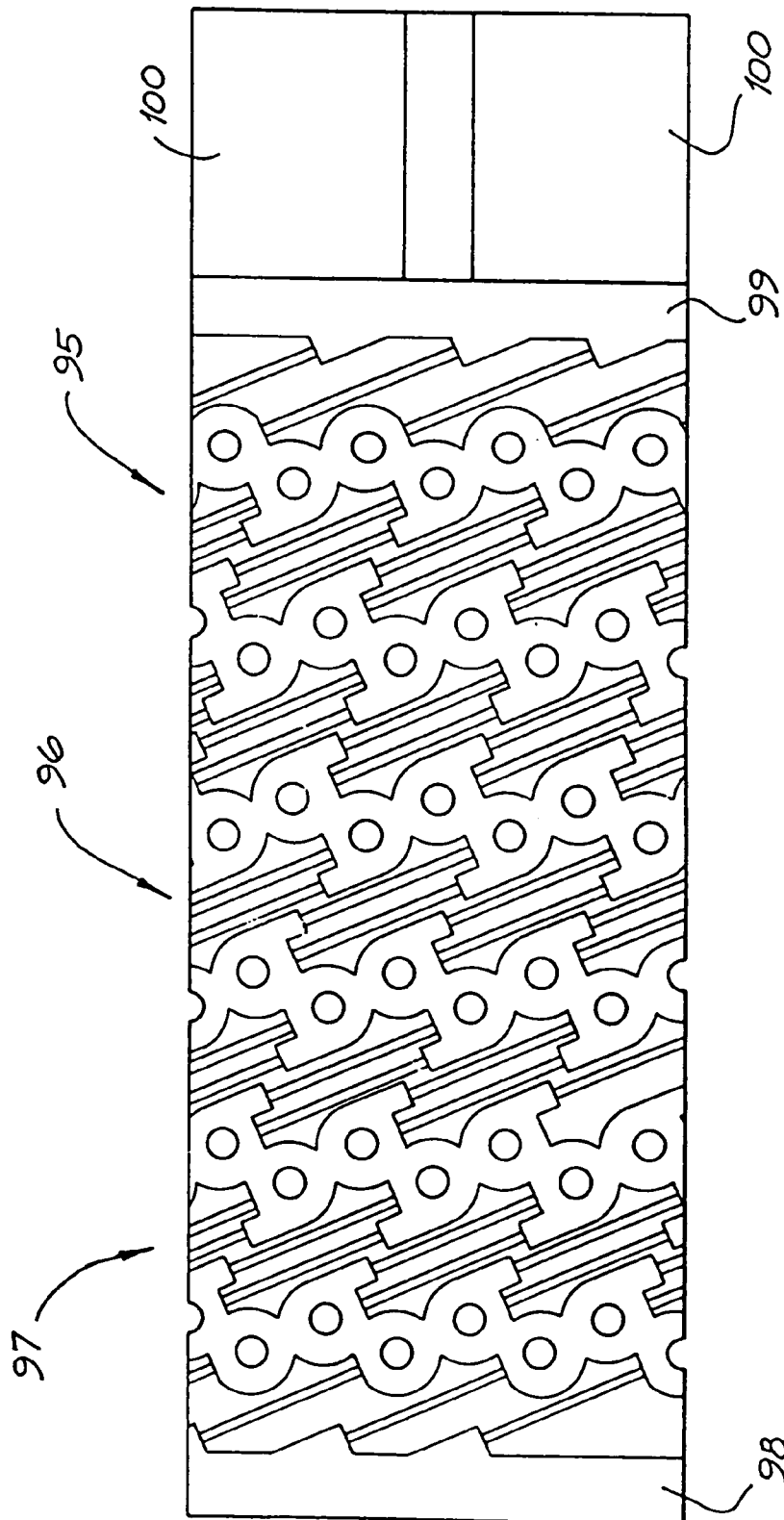


FIG. 18



























 Silicon	 Sacrificial material	 Elastomer
 Boron doped silicon	 Cupronickel	 Polyimide
 Silicon nitride (Si ₃ N ₄)	 CoNiFe or NiFe	 Indium tin oxide (ITO)
 CMOS device region	 Permanent magnet	 PTFE
 Aluminum	 Polysilicon	 Conductive PTFE
 Glass (SiO ₂)	 Titanium Nitride (TiN)	 Terfenol-D
 Copper	 Titanium boride (TiB ₂)	 Shape memory alloy
 Gold	 Adhesive	 Tantalum
	 Resist	 Ink

FIG. 19

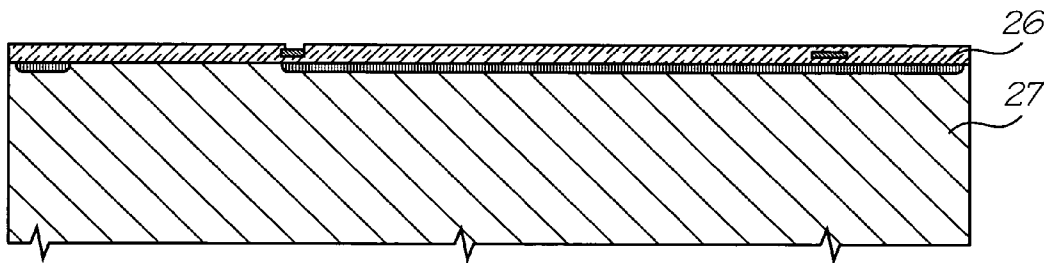


FIG. 20

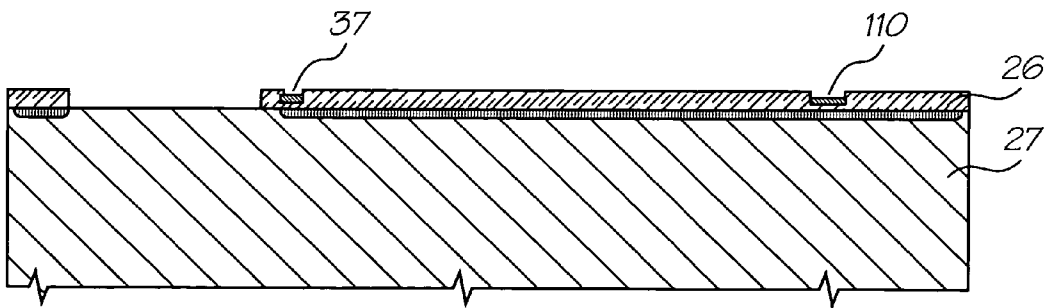


FIG. 21

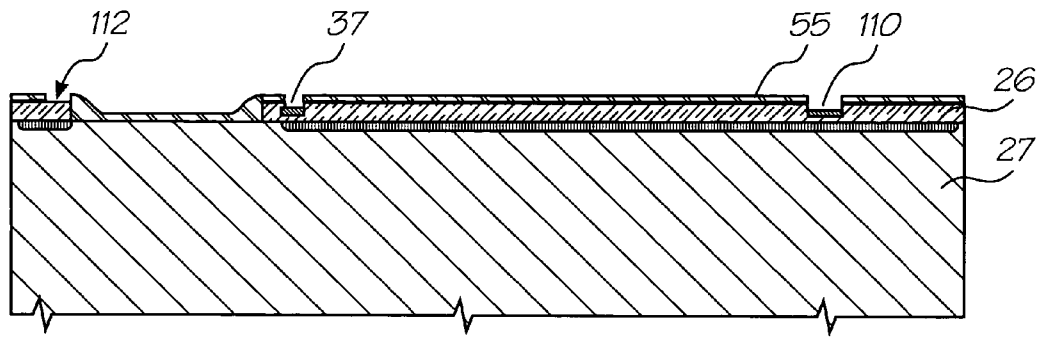


FIG. 22

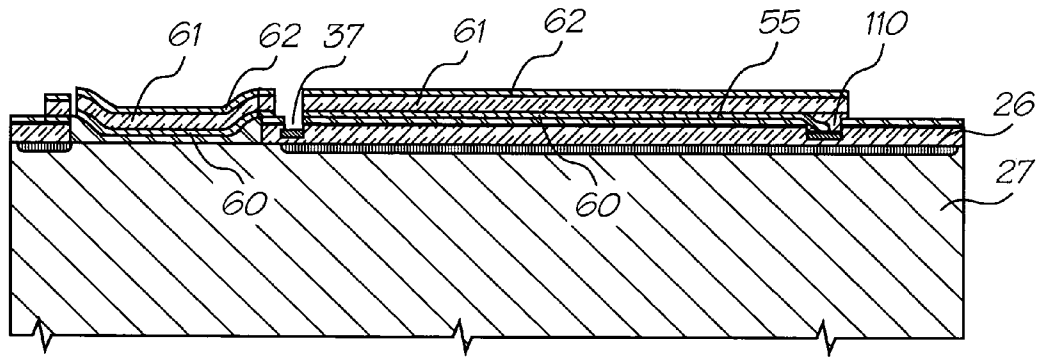


FIG. 23

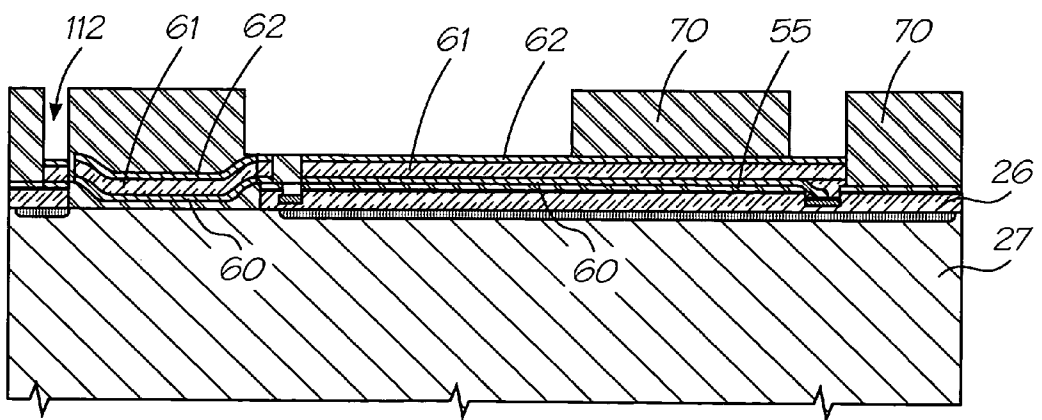


FIG. 24

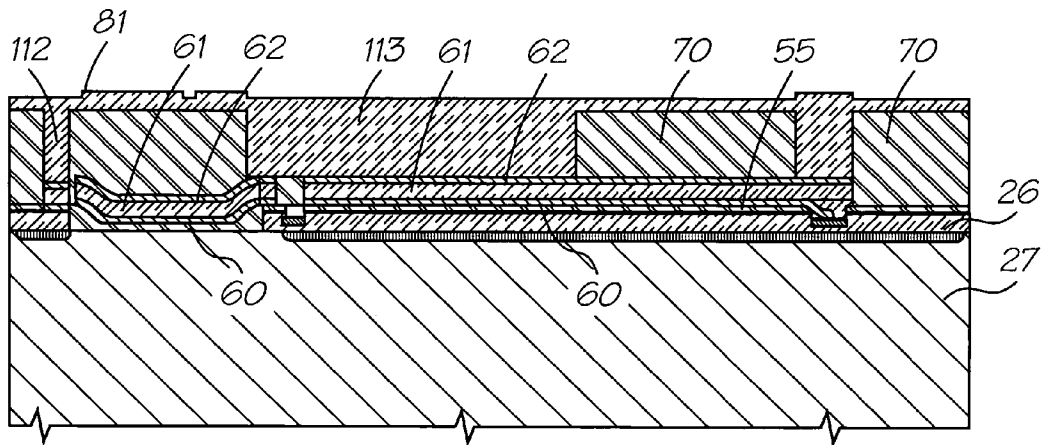


FIG. 25

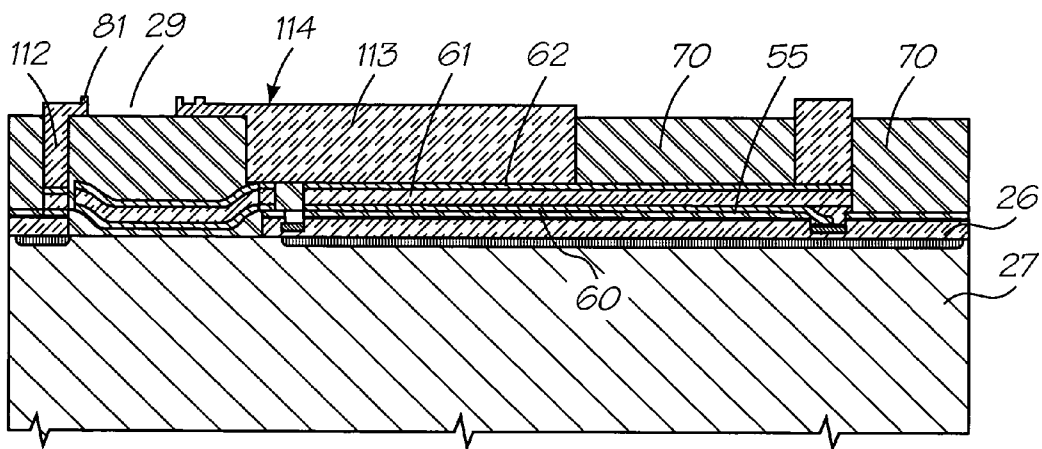


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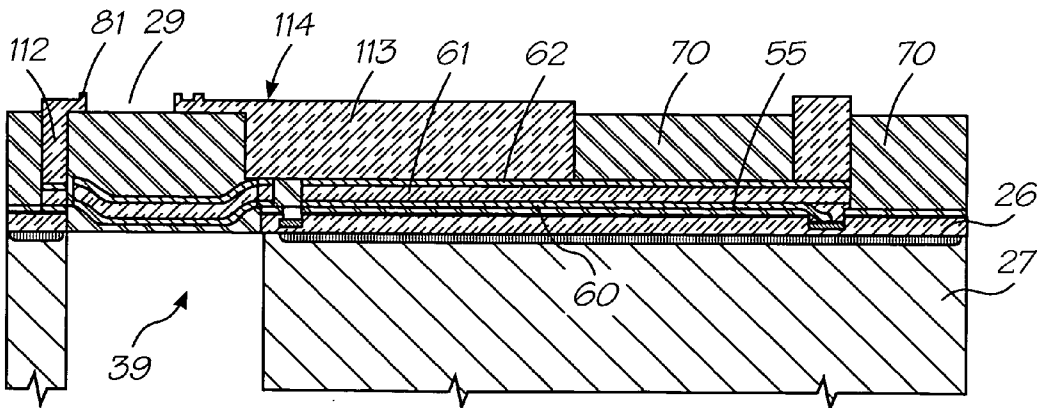


FIG. 27

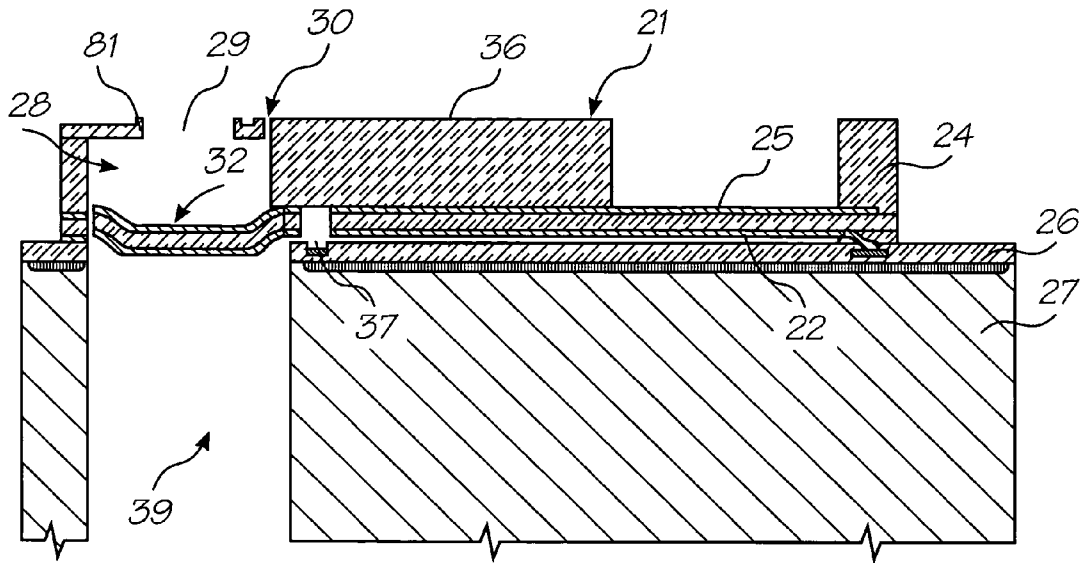


FIG. 28

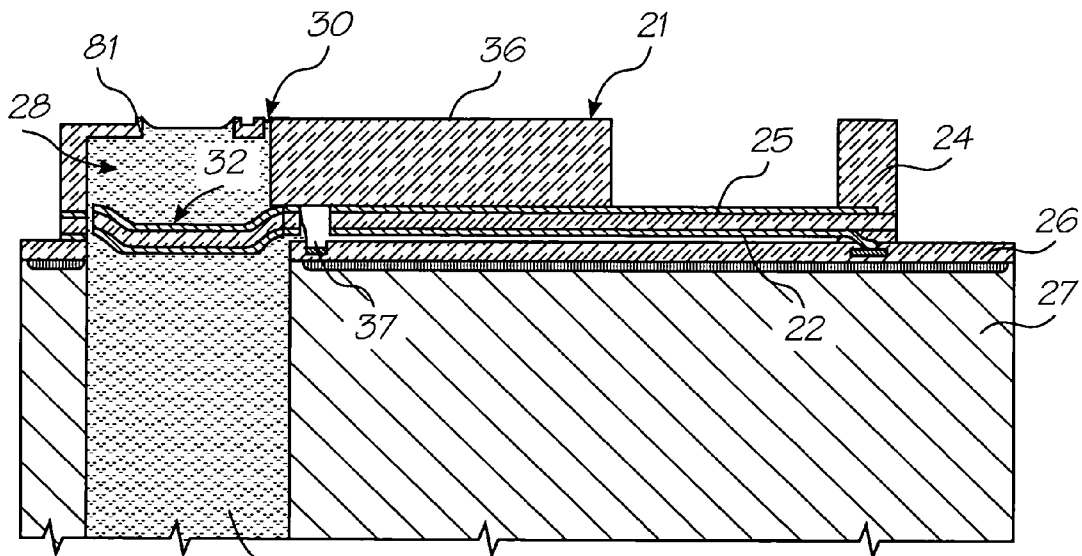


FIG. 29

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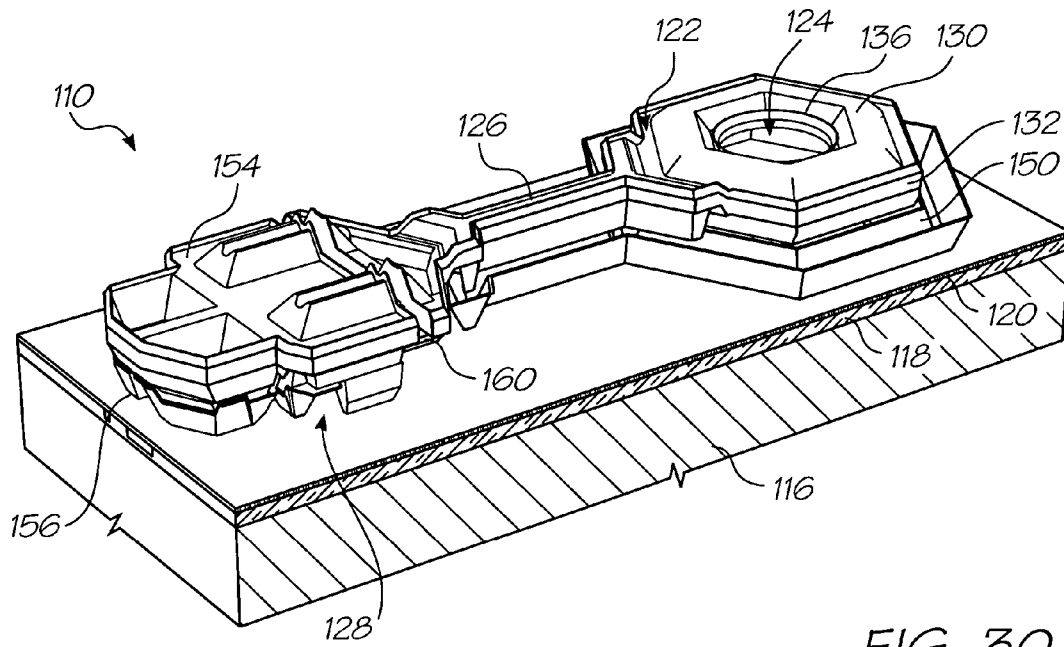


FIG. 30

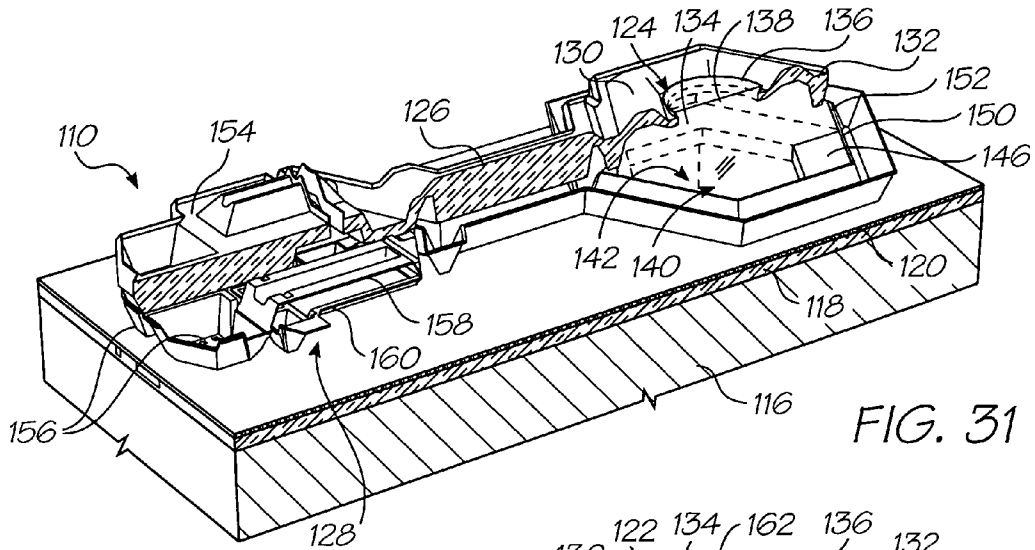


FIG. 31

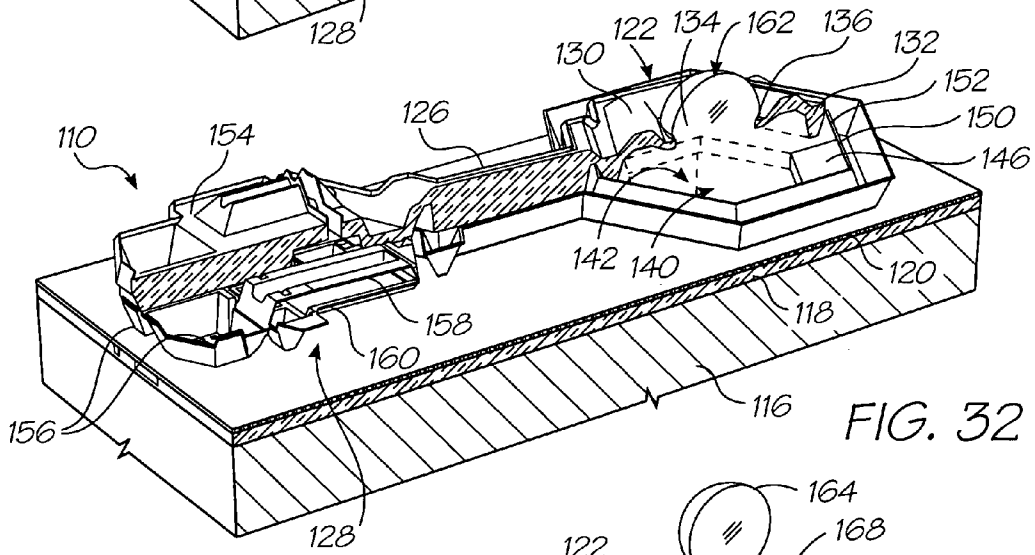


FIG. 32

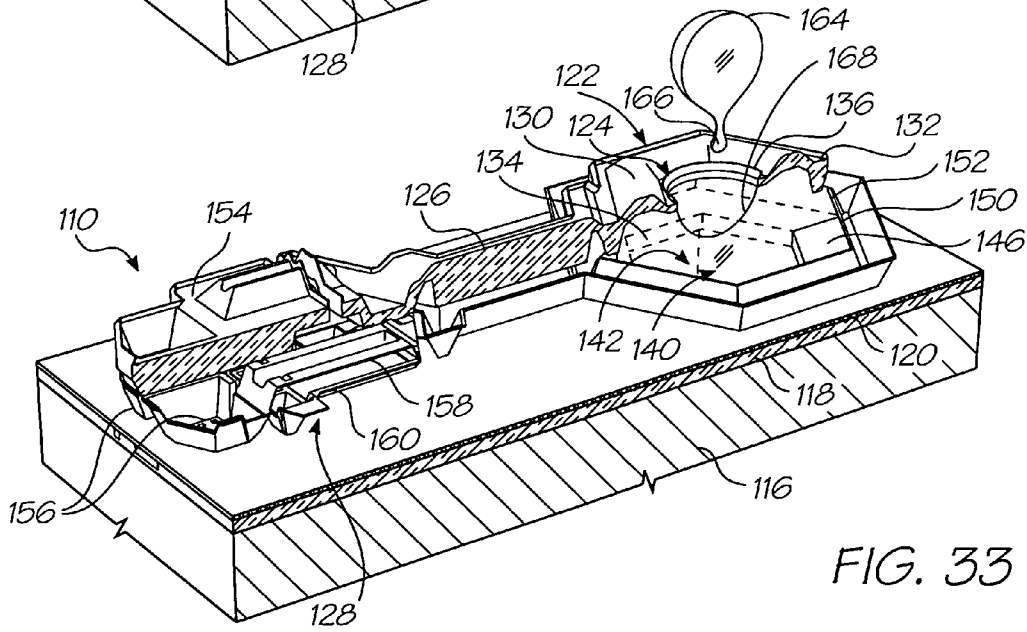


FIG. 33

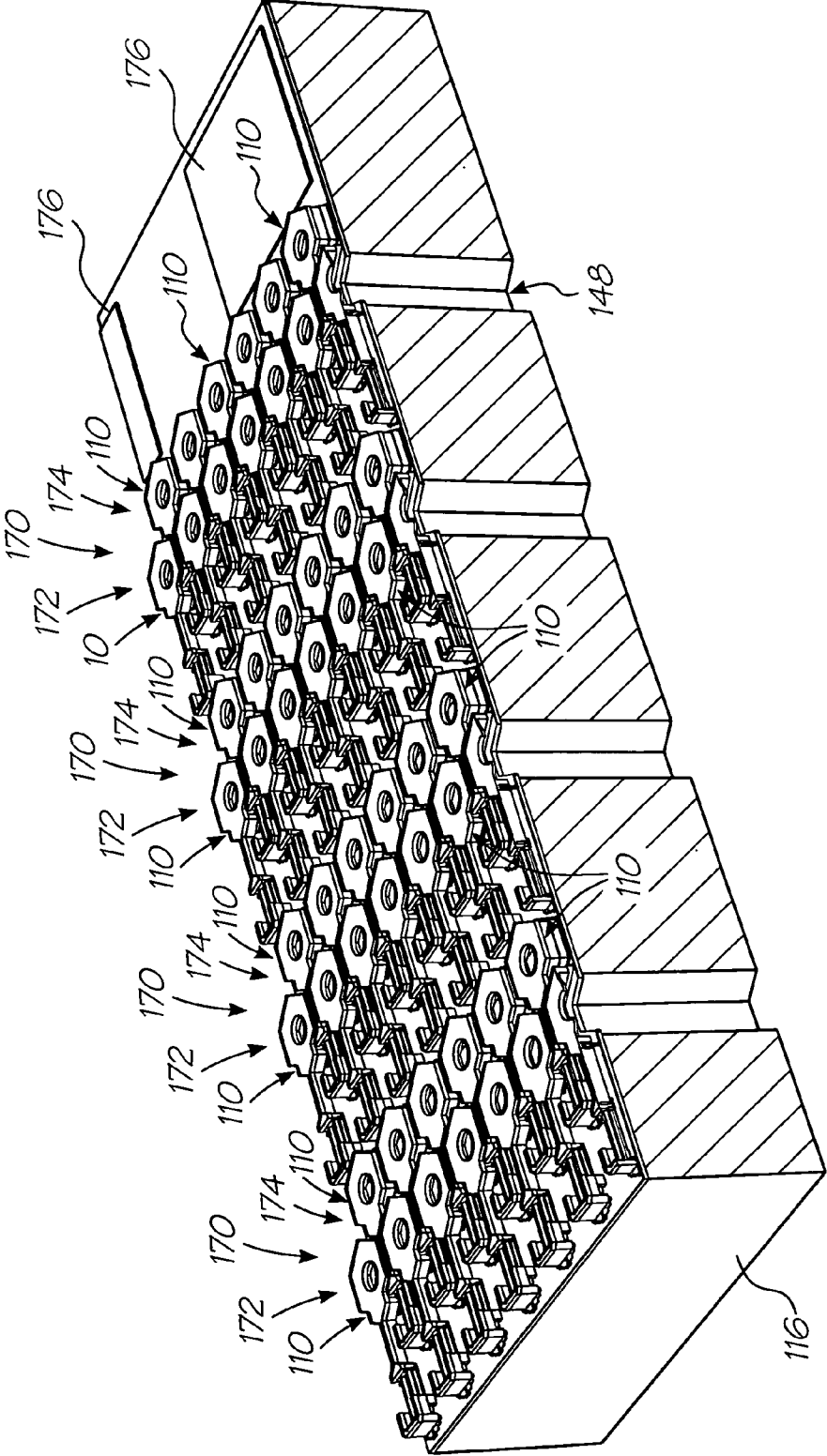


FIG. 34

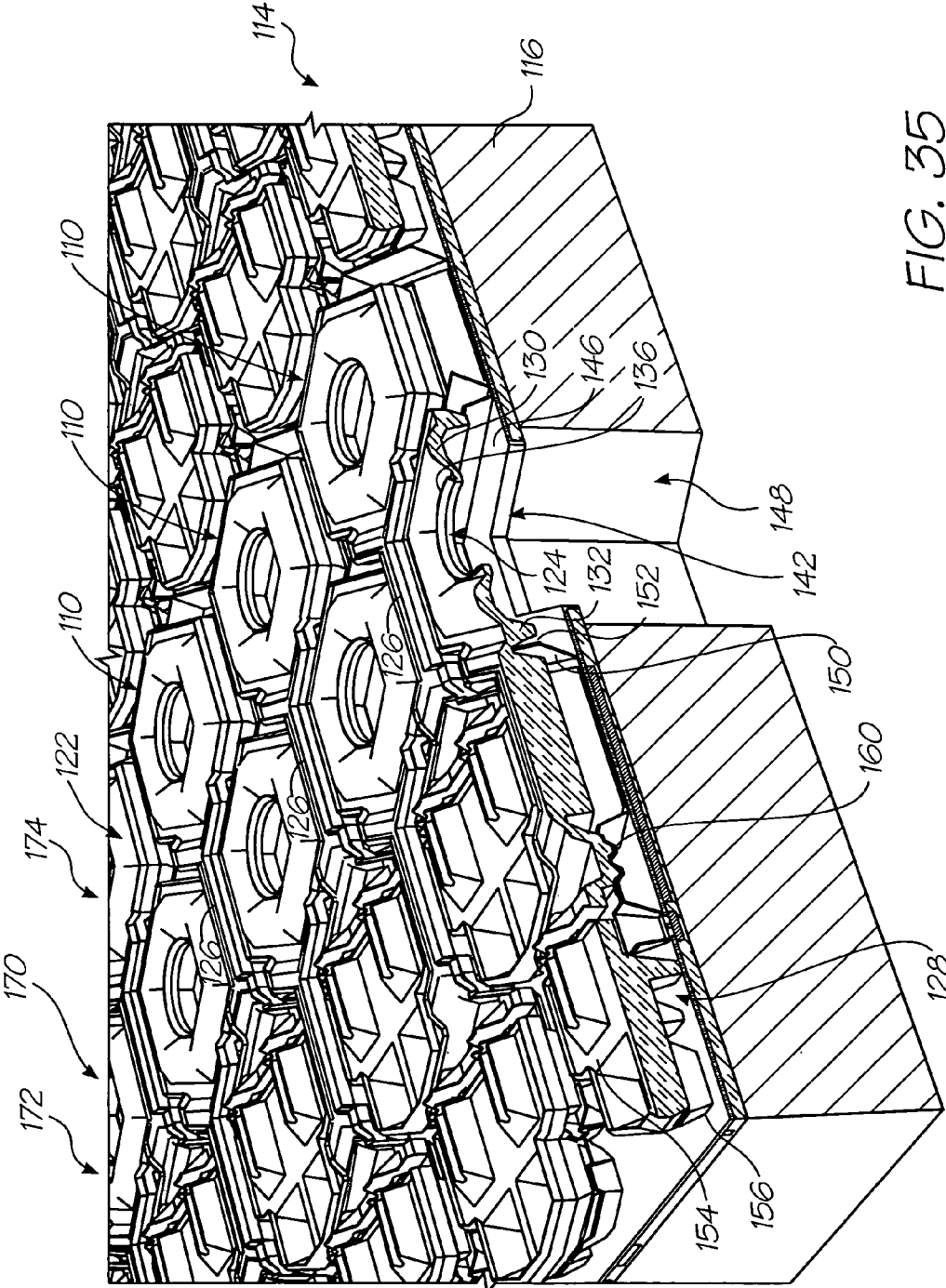


FIG. 35

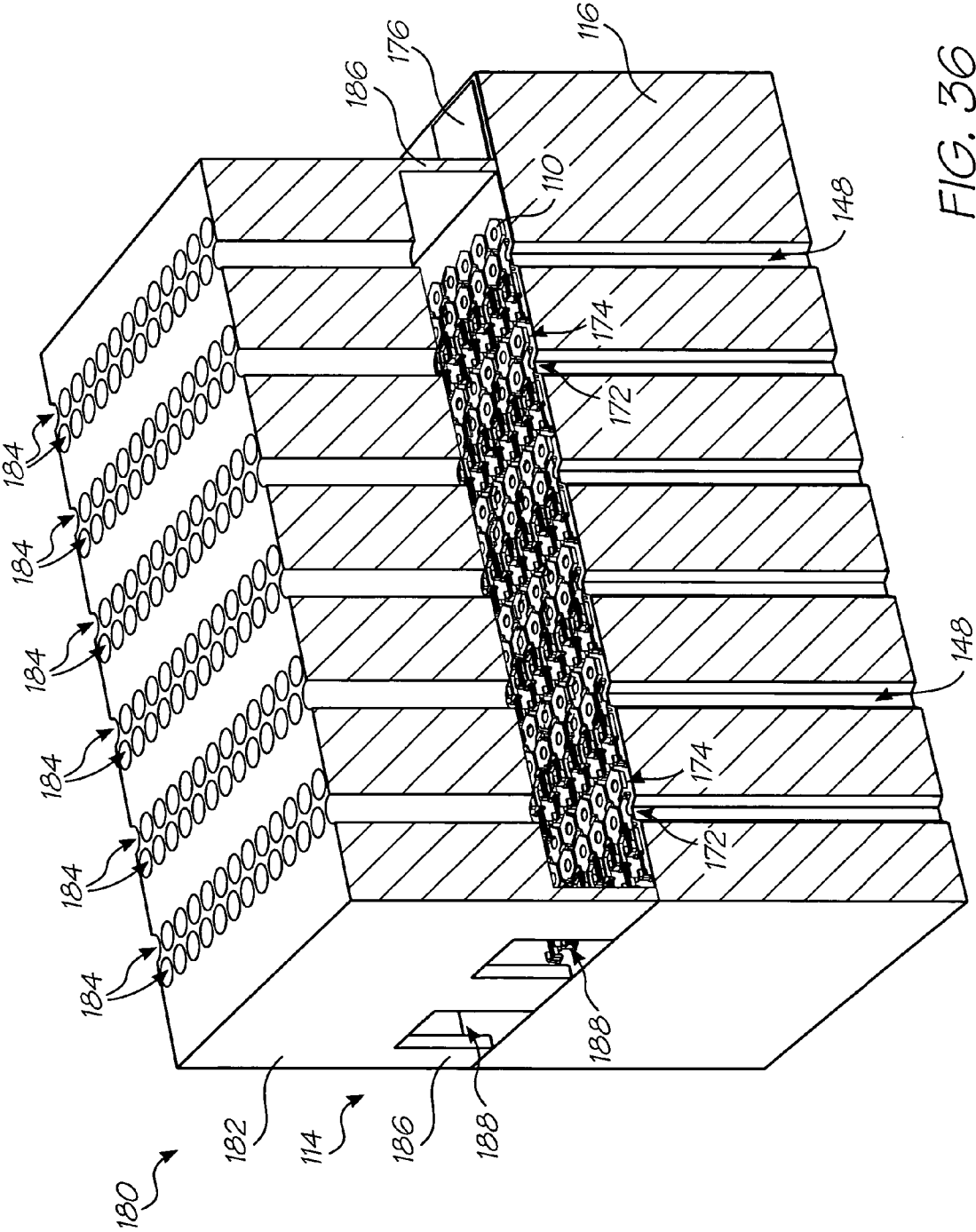
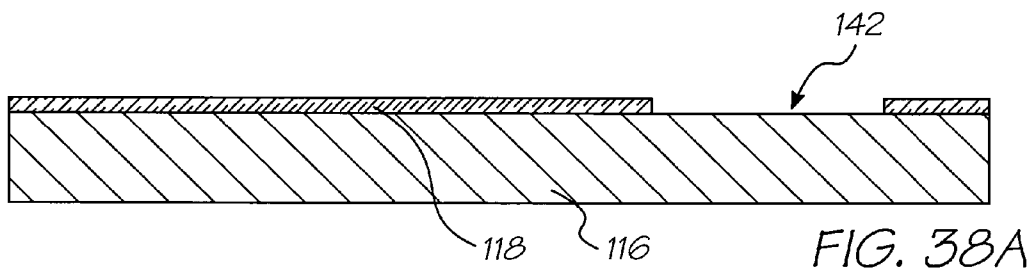
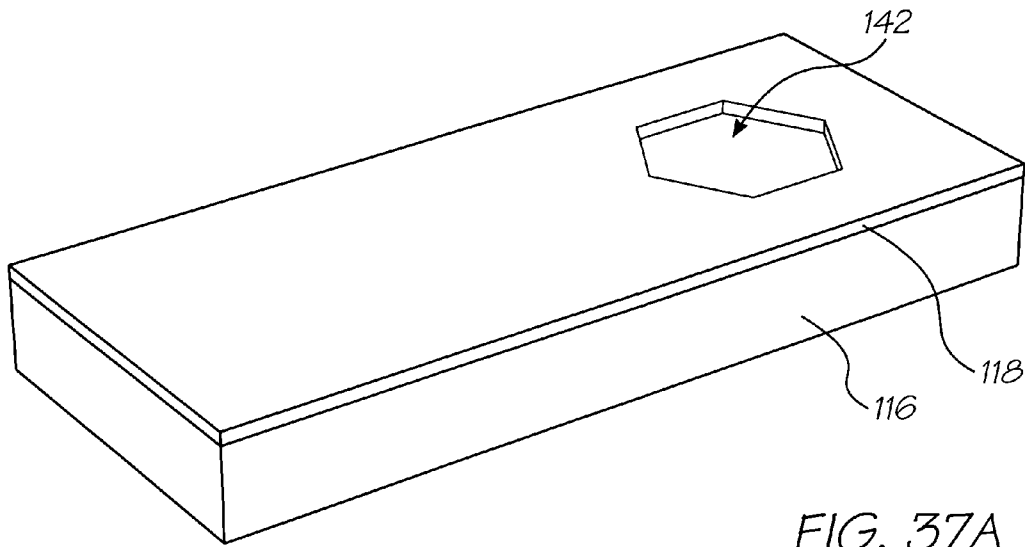
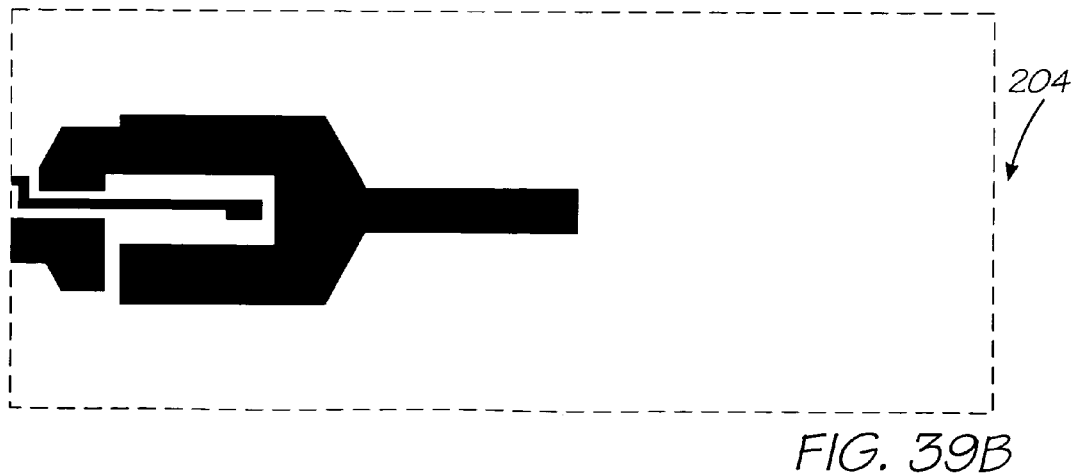
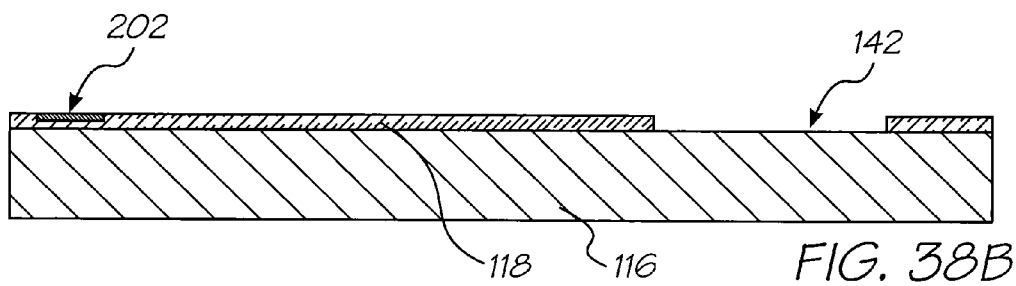
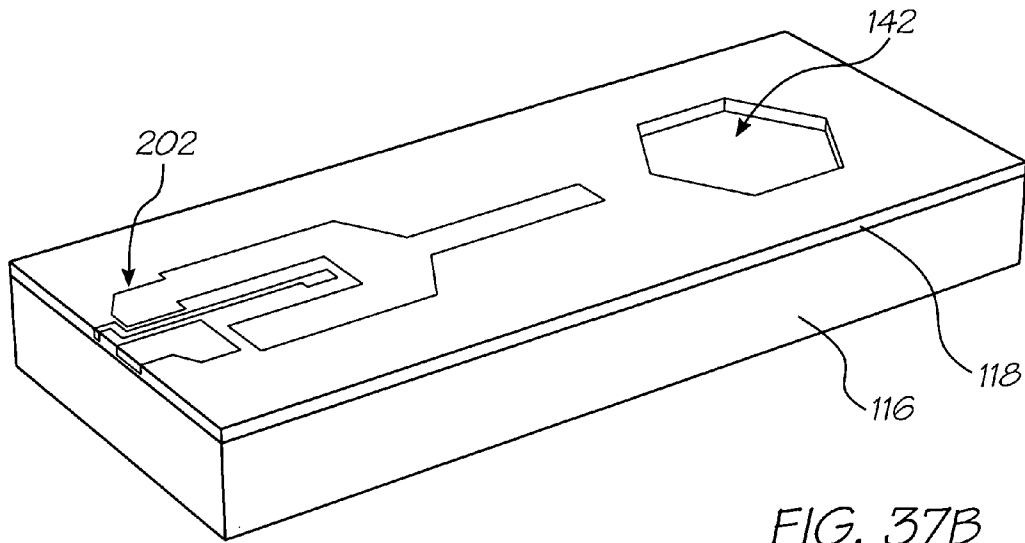
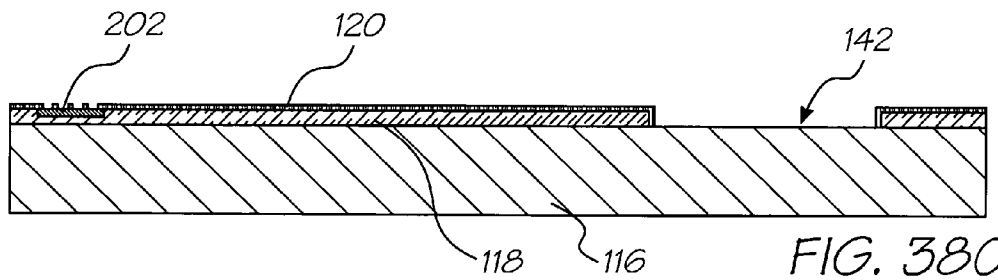
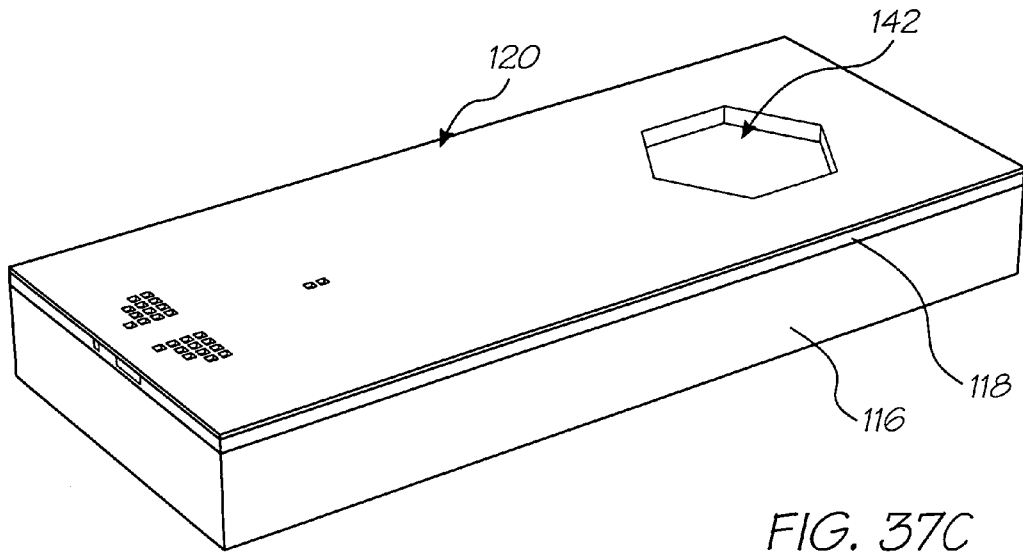


FIG. 36







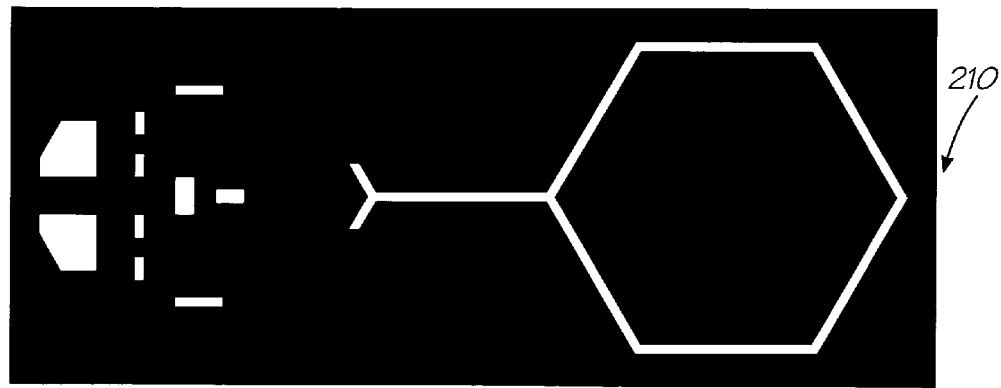
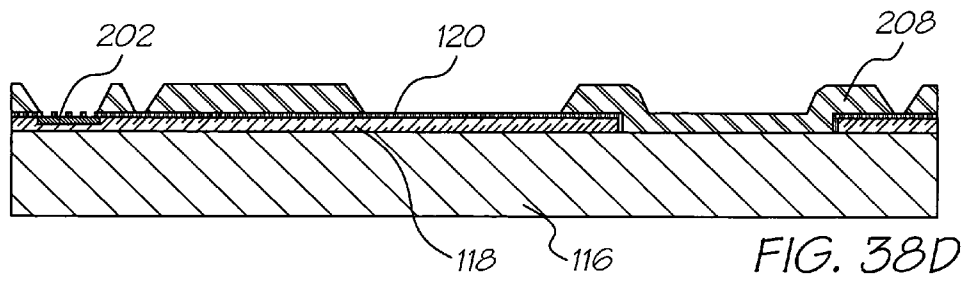
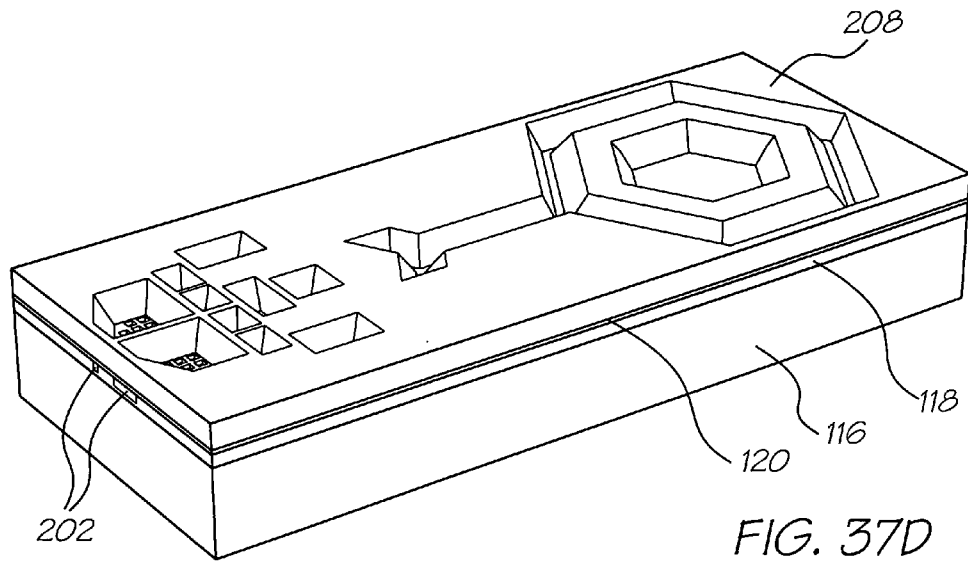


FIG. 39D

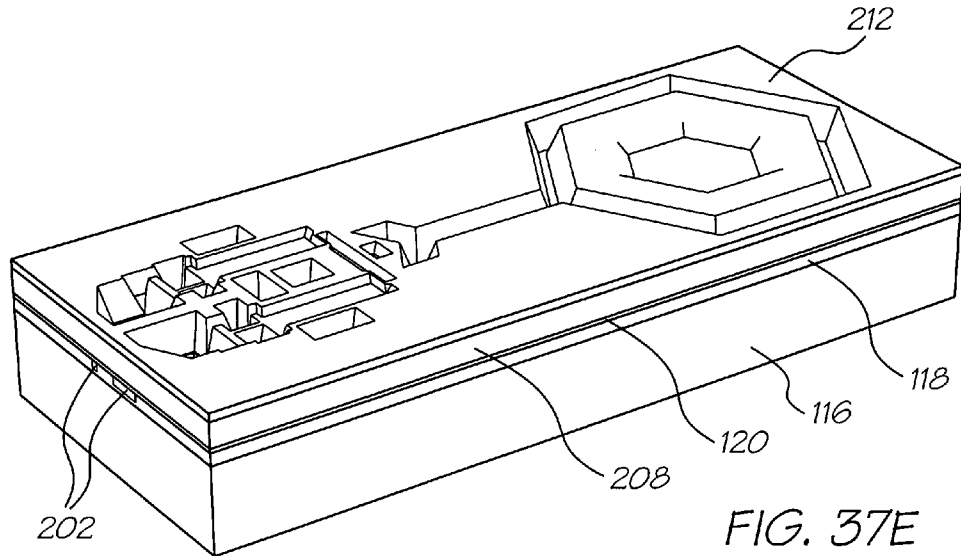


FIG. 37E

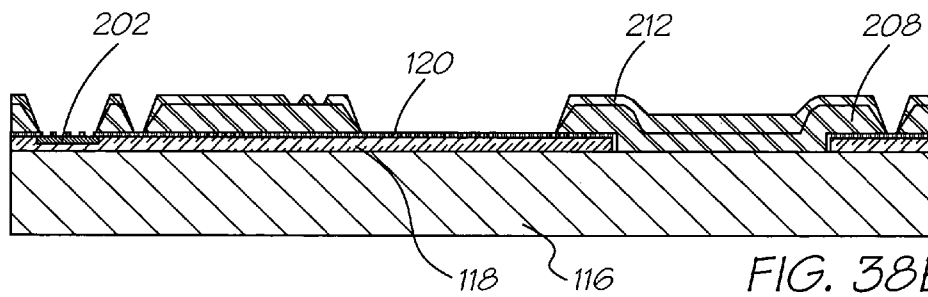


FIG. 38E

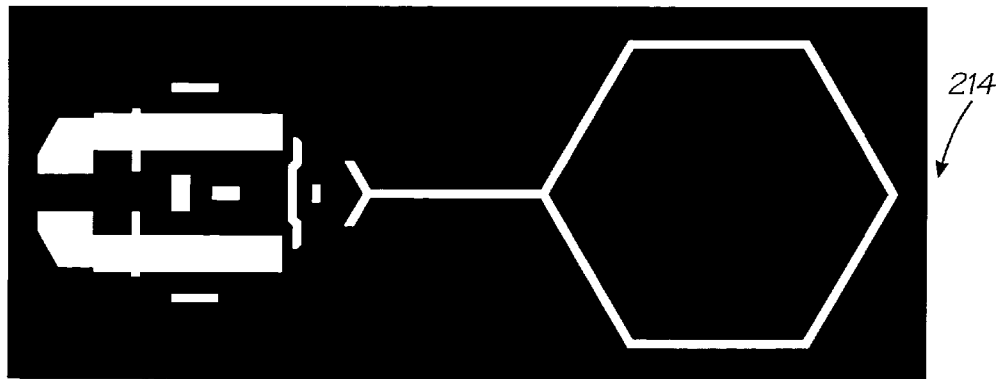


FIG. 39E

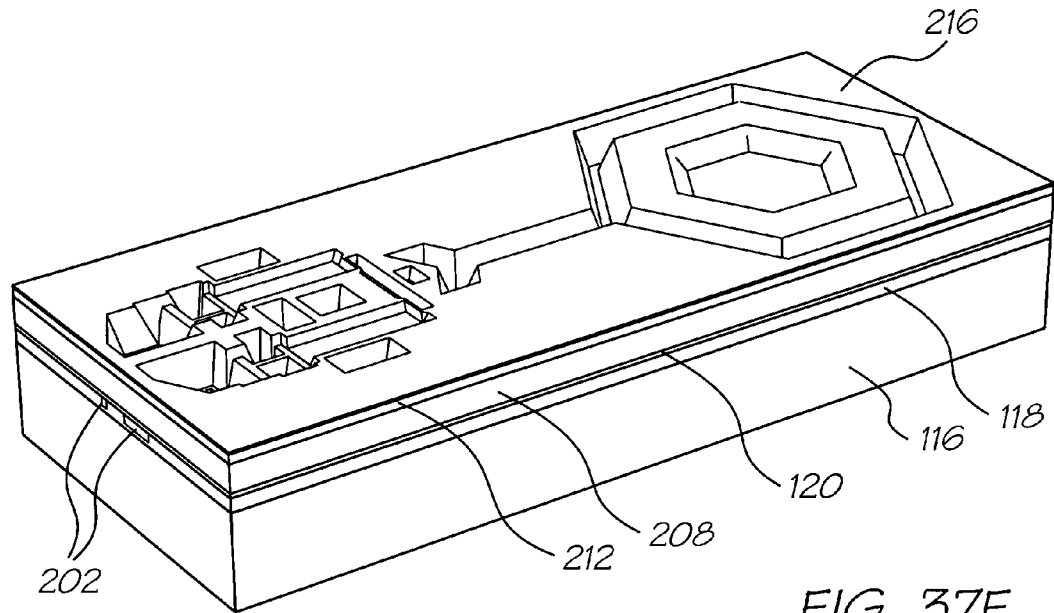


FIG. 37F

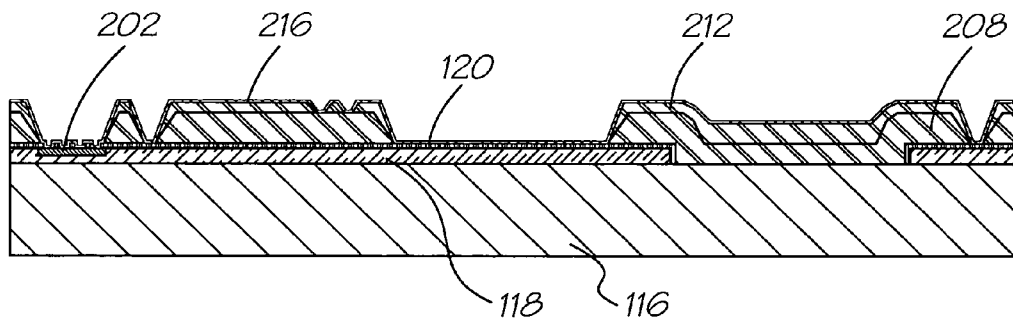
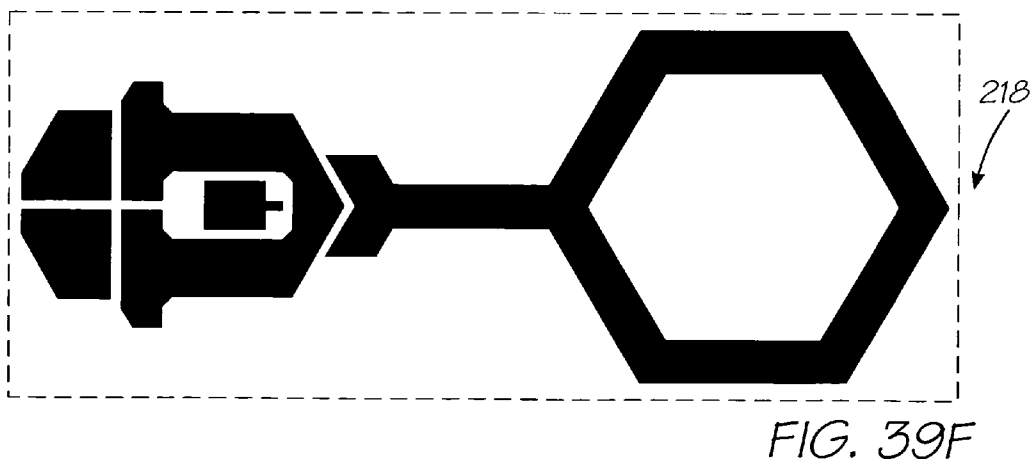
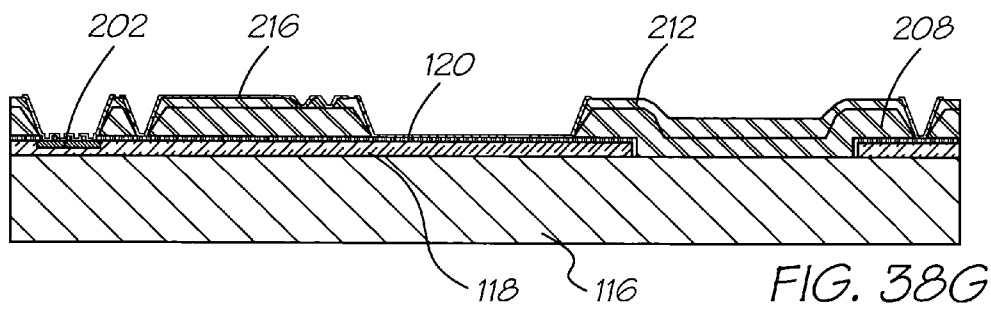
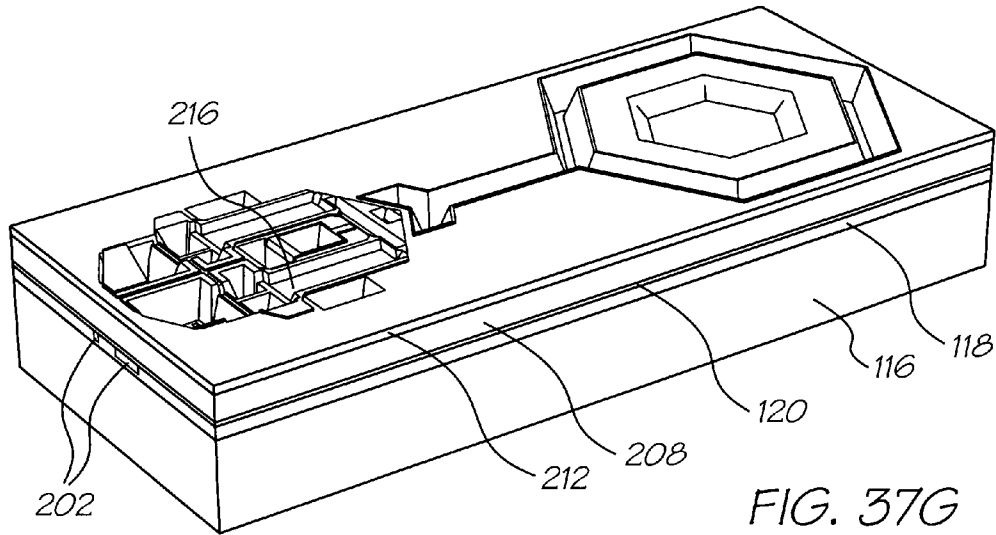
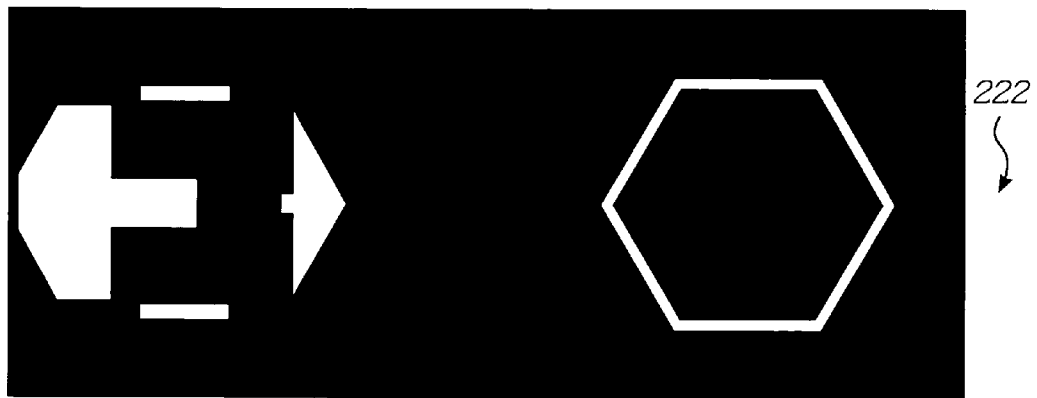
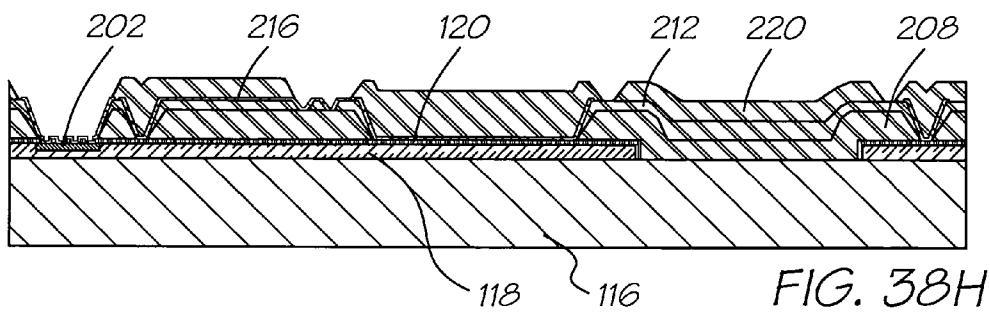
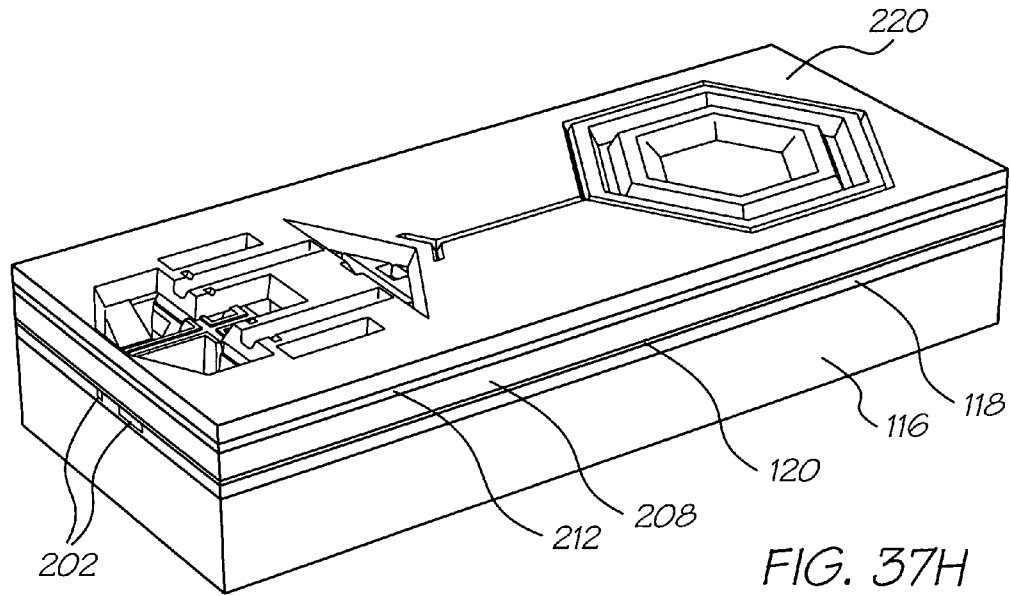


FIG. 38F





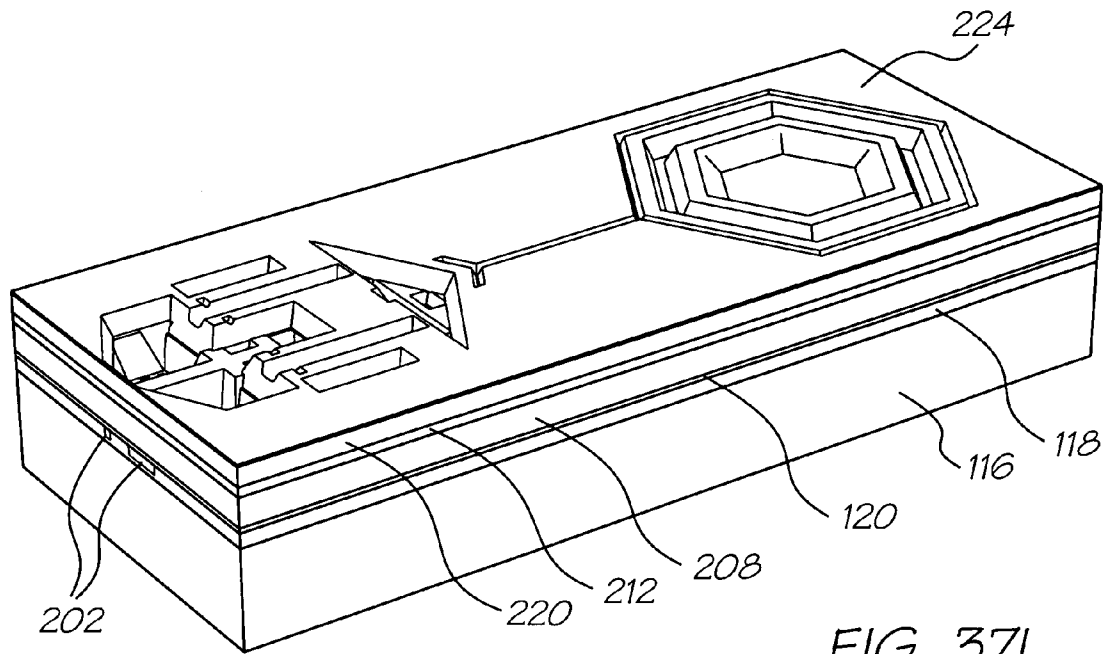


FIG. 371

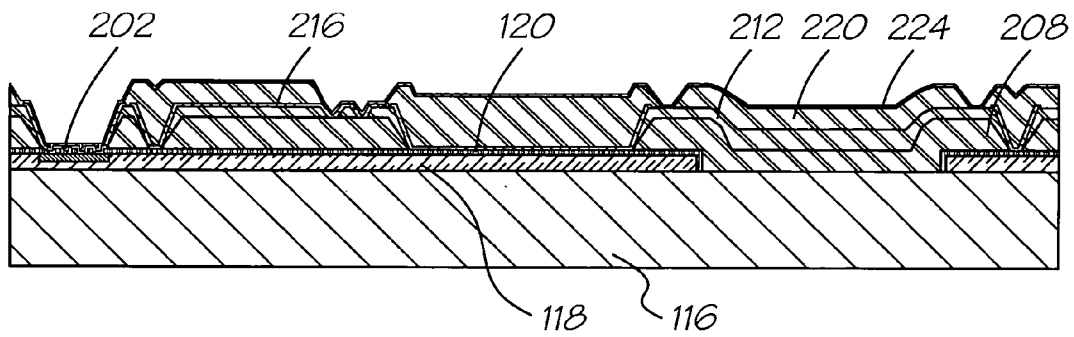


FIG. 381

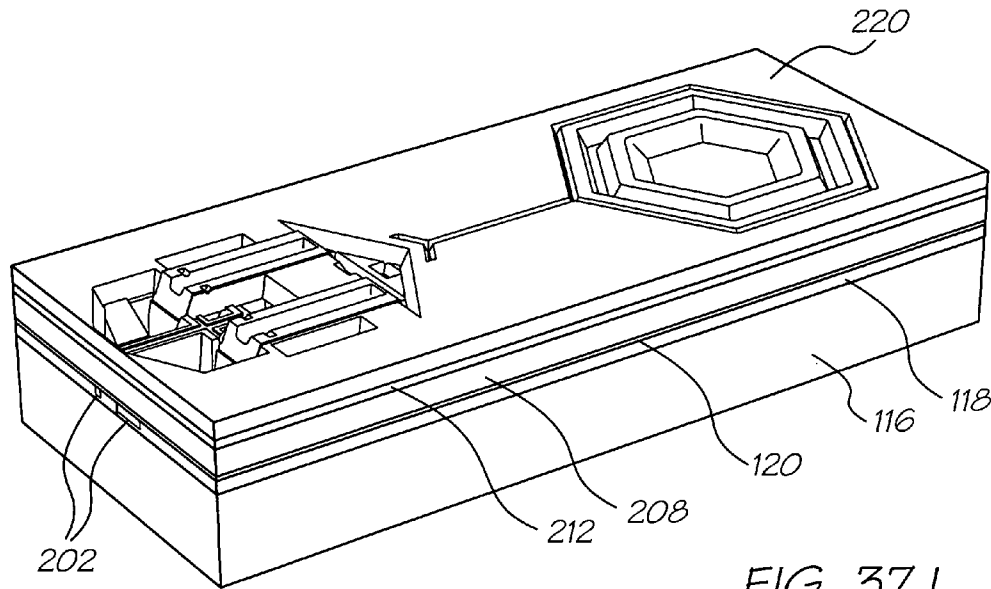


FIG. 37J

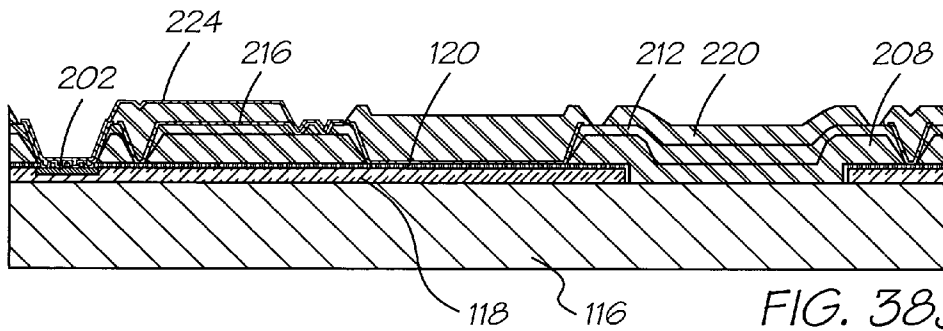


FIG. 38J

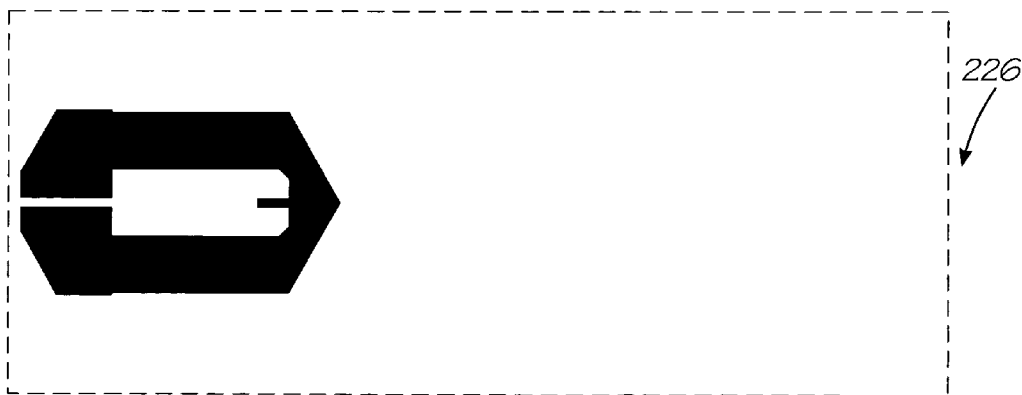


FIG. 39H

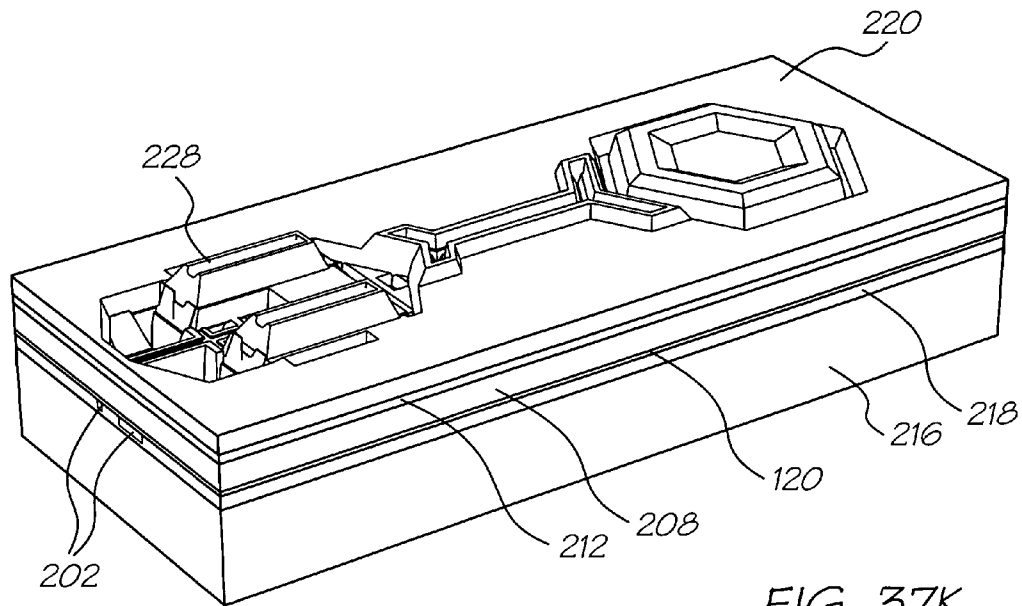


FIG. 37K

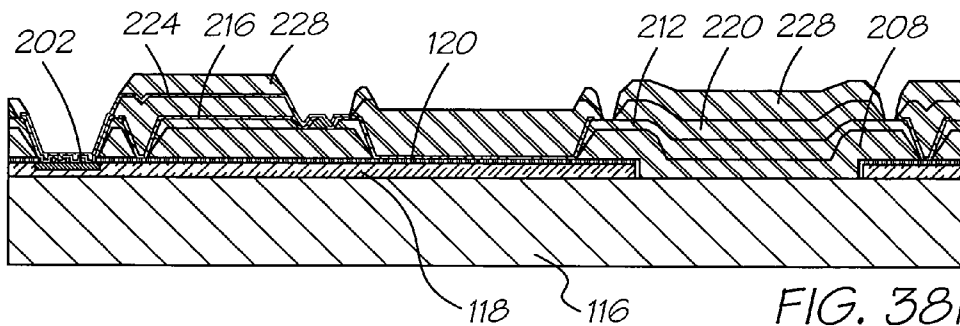


FIG. 38K

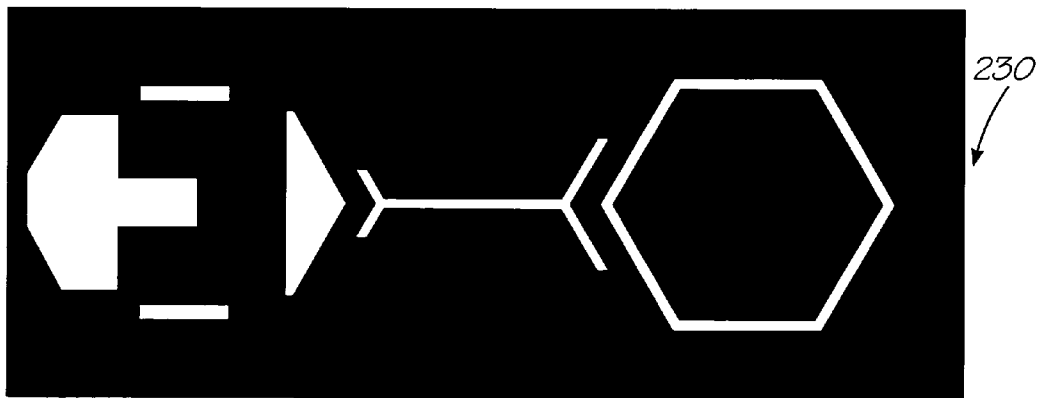


FIG. 39I

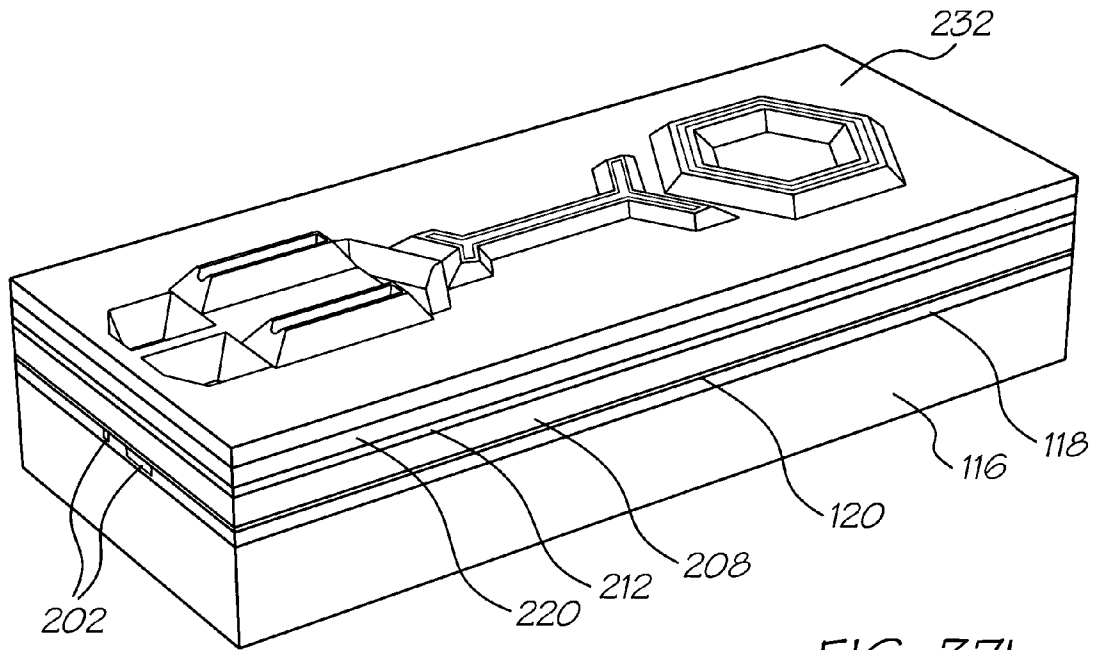


FIG. 37L

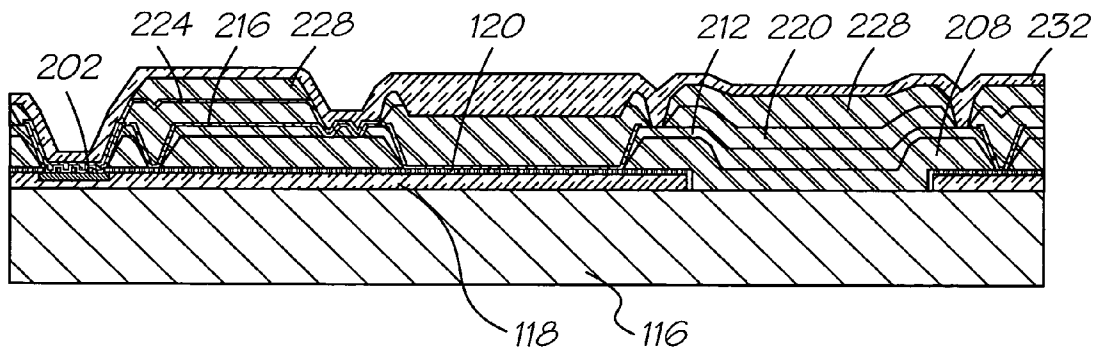
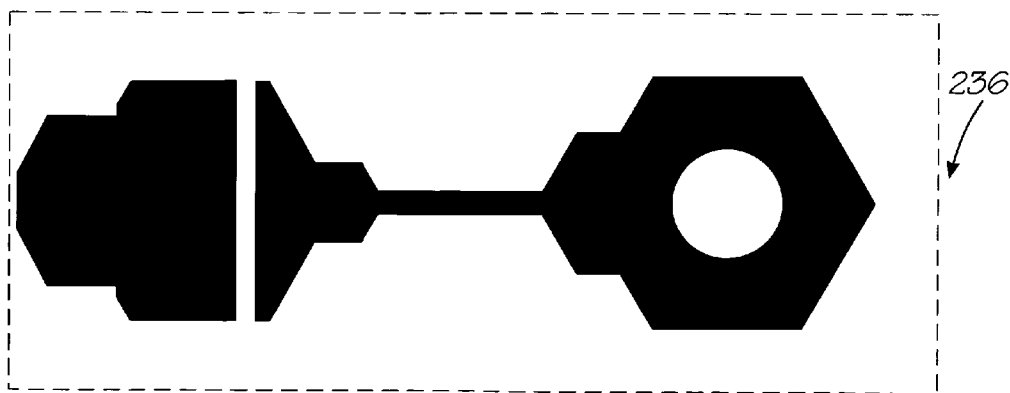
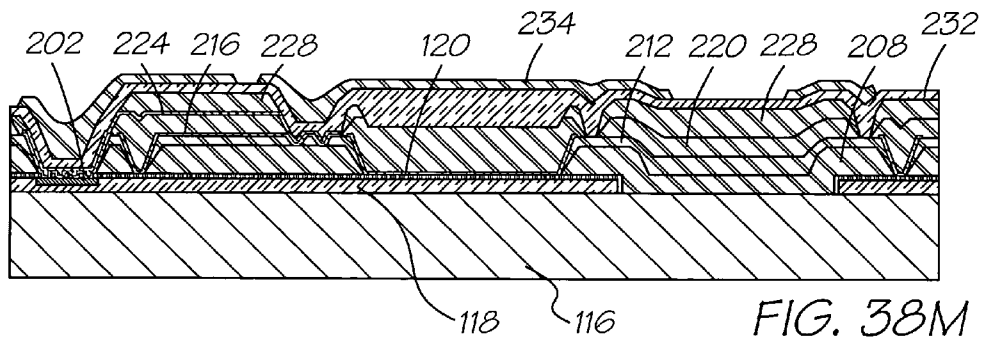
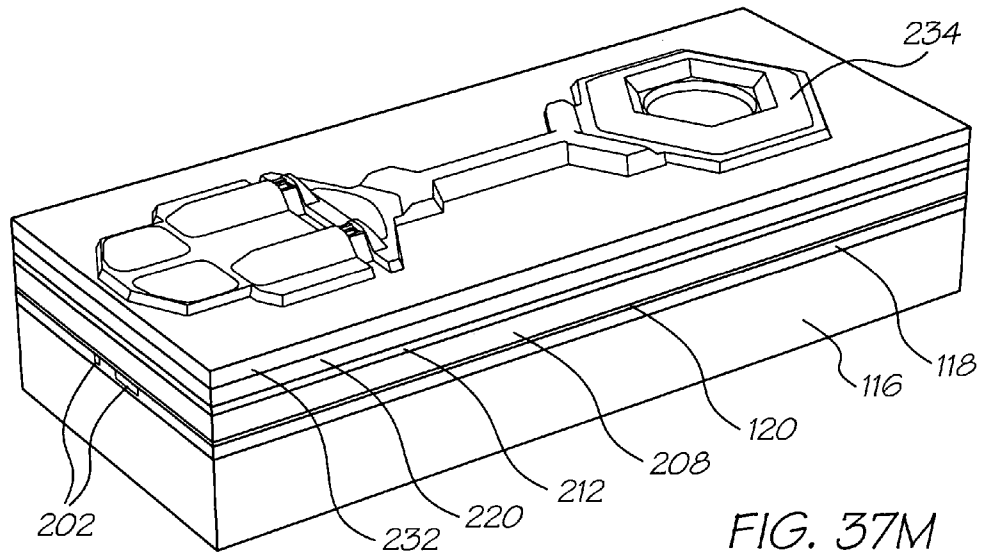
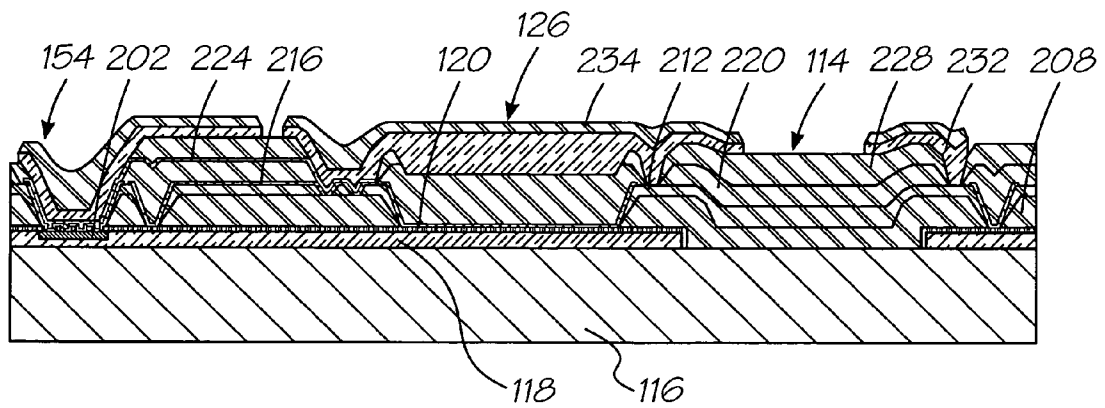
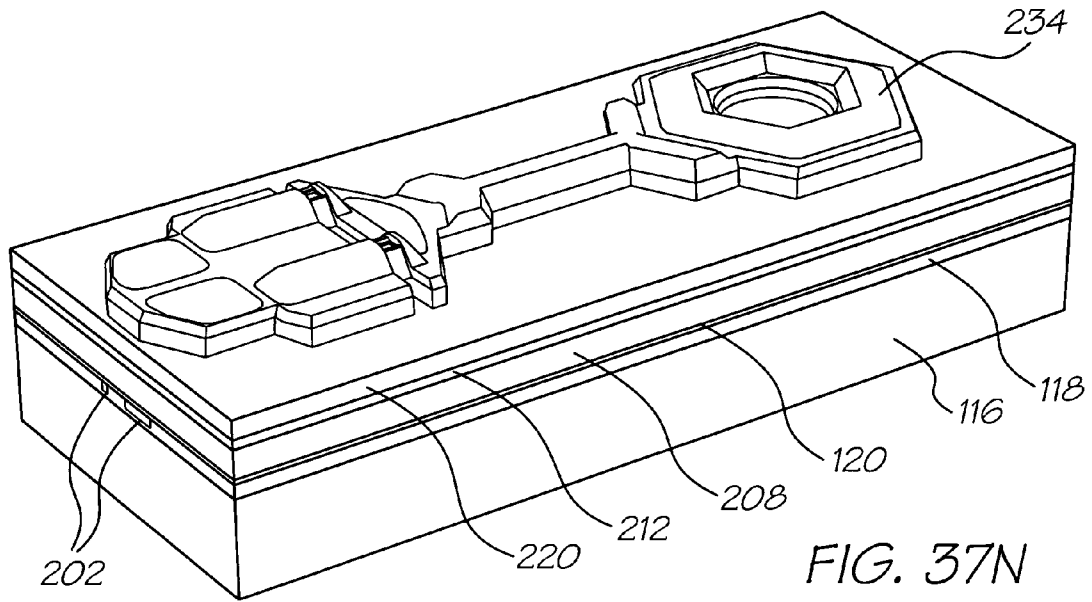


FIG. 38L





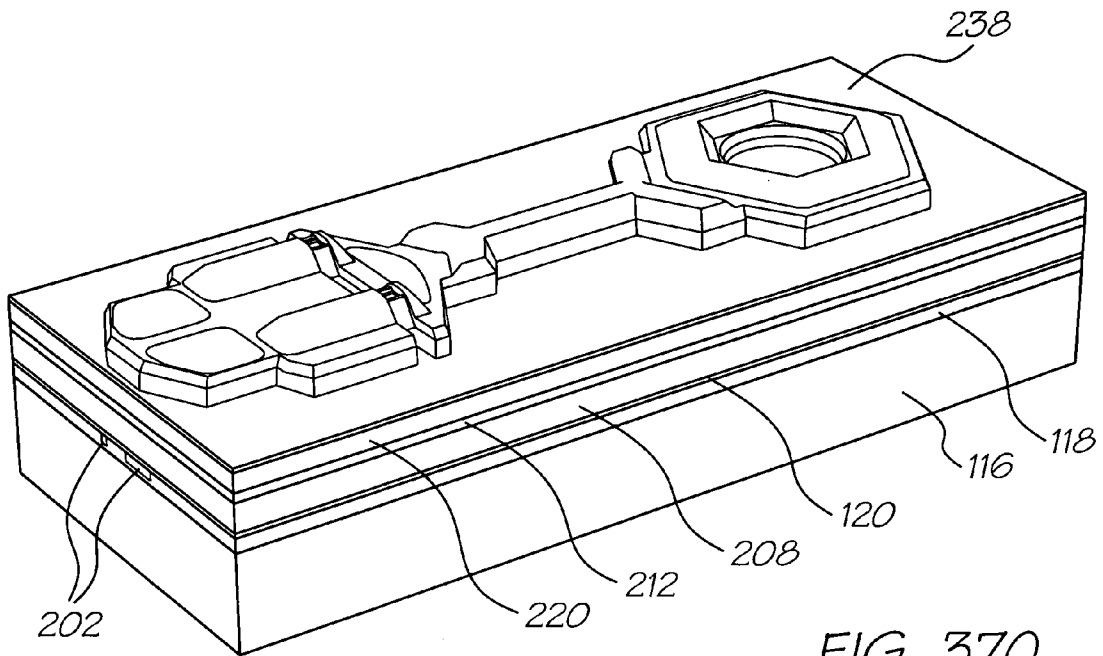


FIG. 370

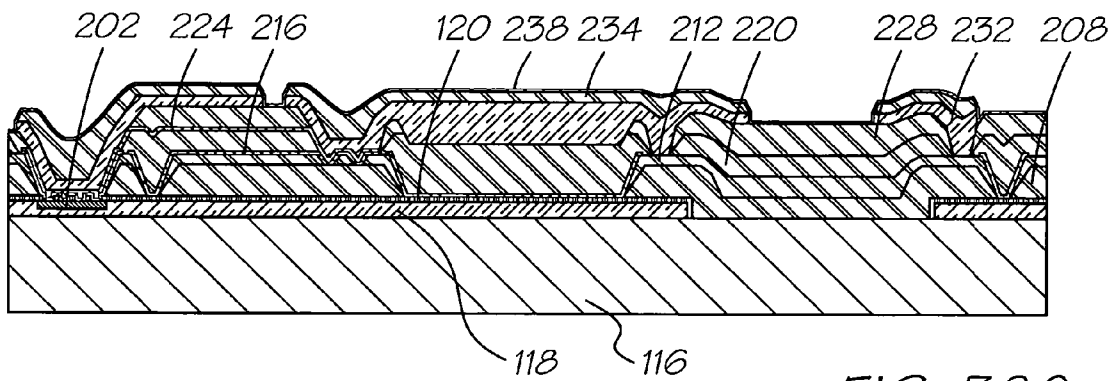
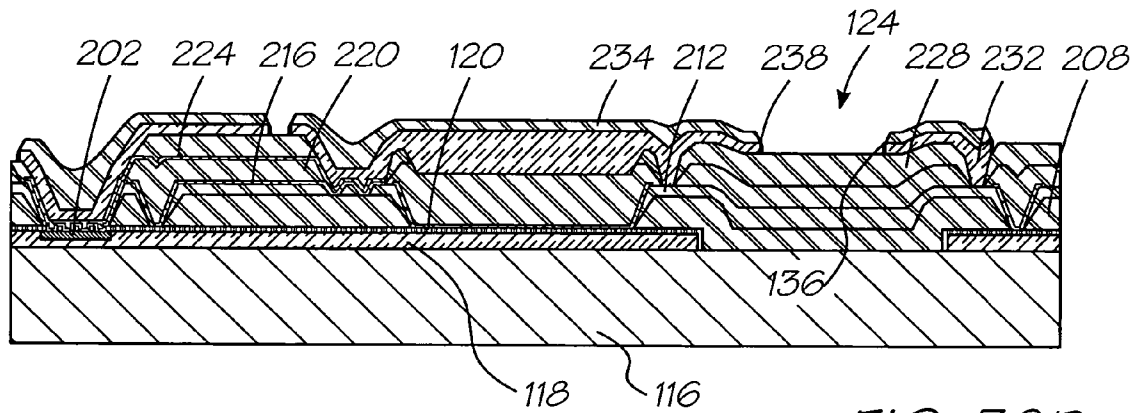
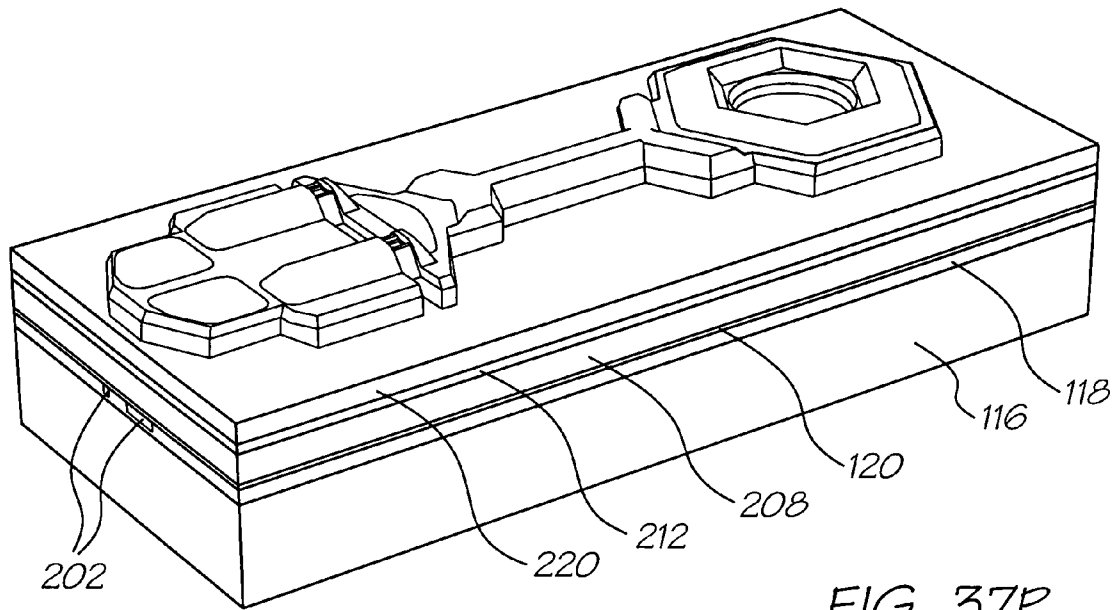


FIG. 380



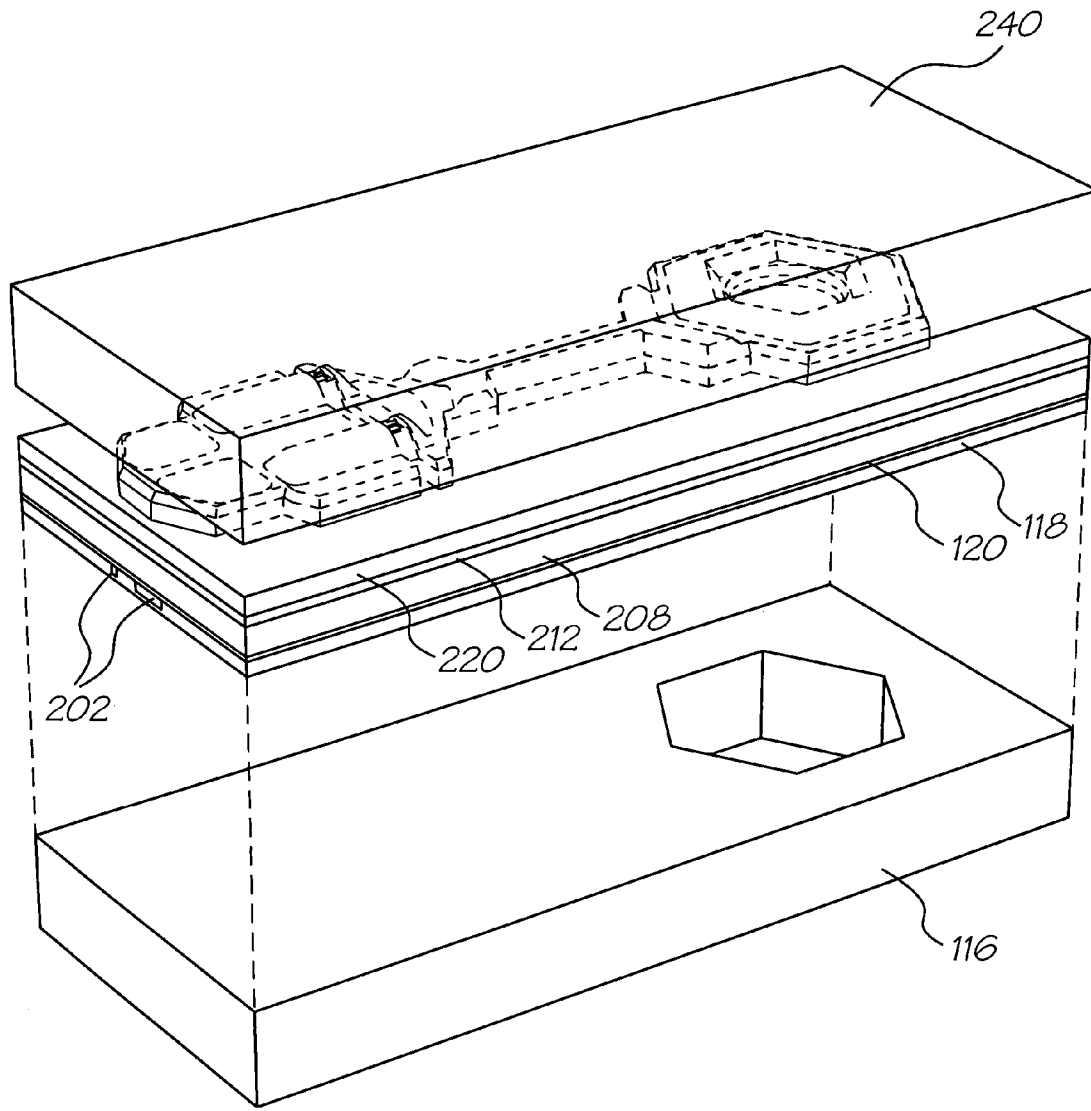


FIG. 37Q

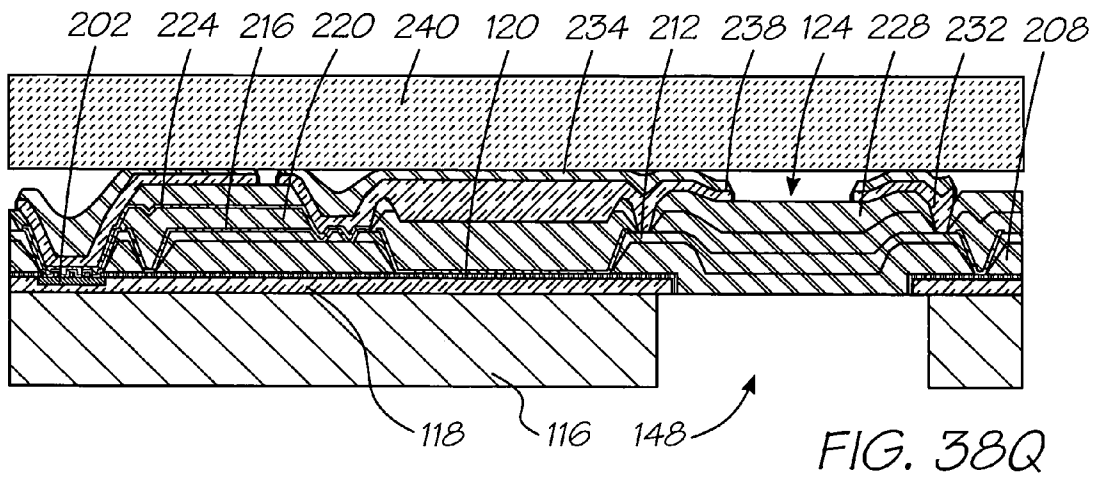


FIG. 38Q

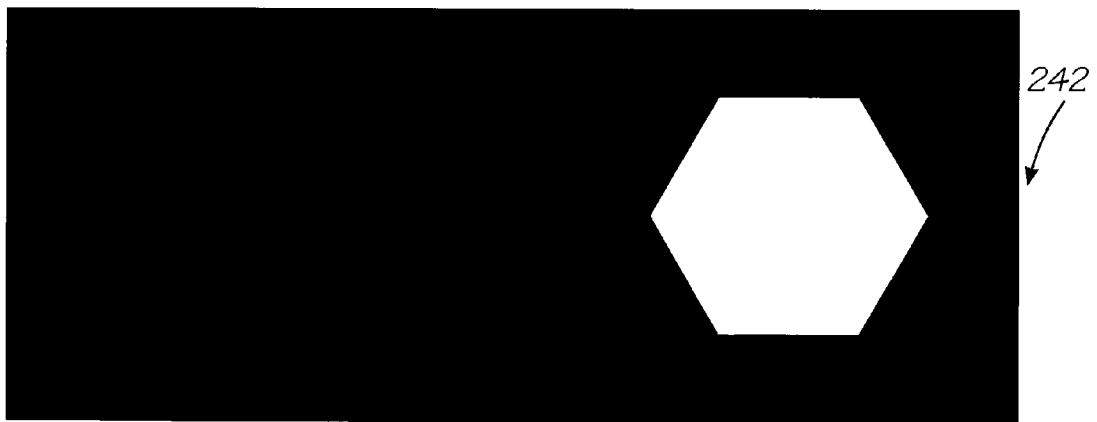


FIG. 39K

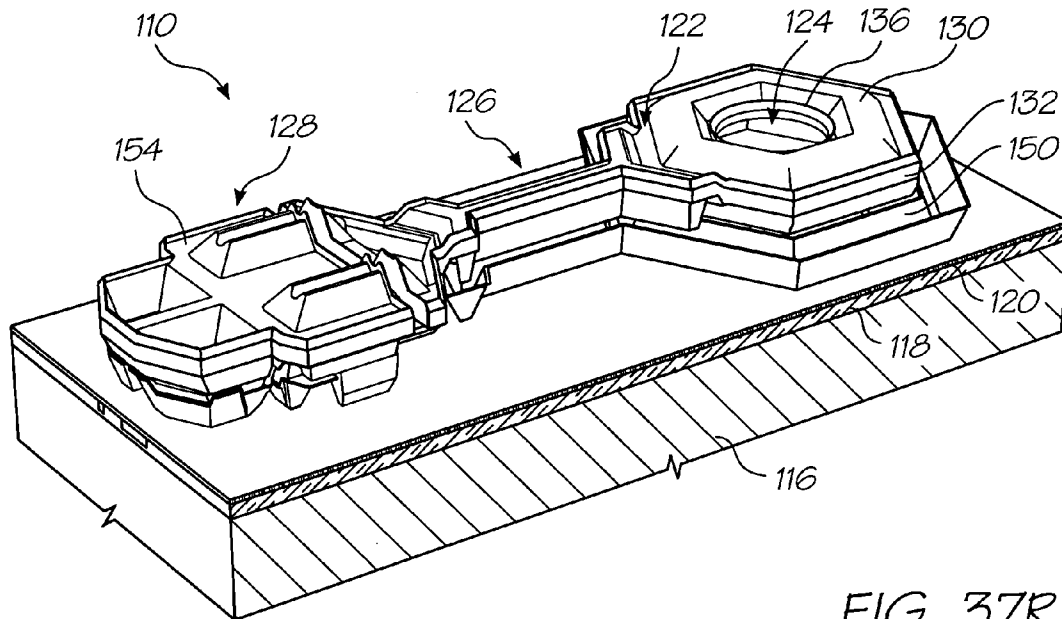


FIG. 37R

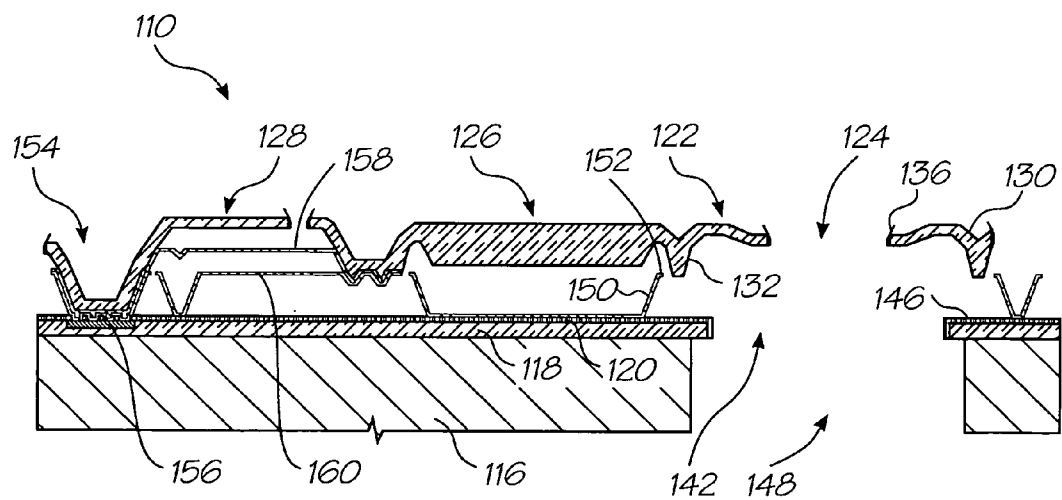
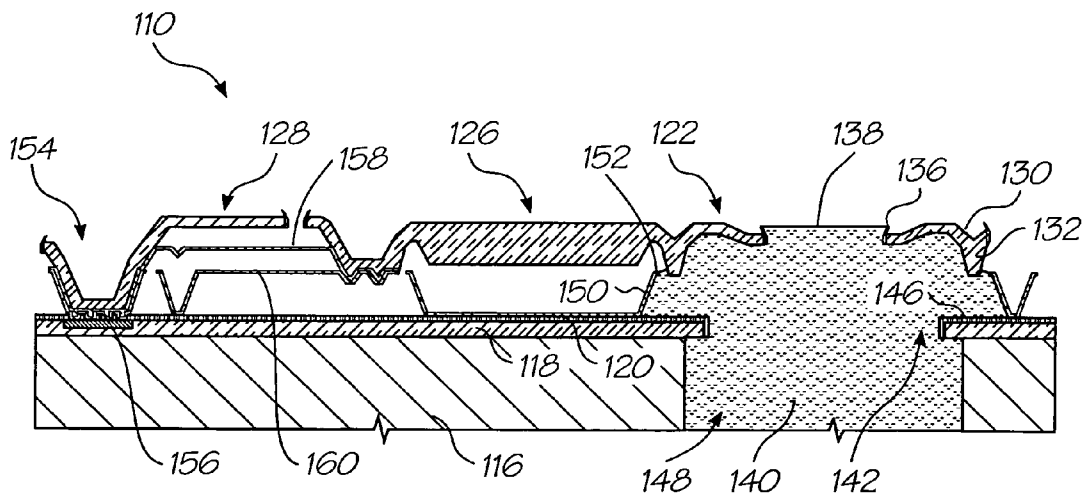
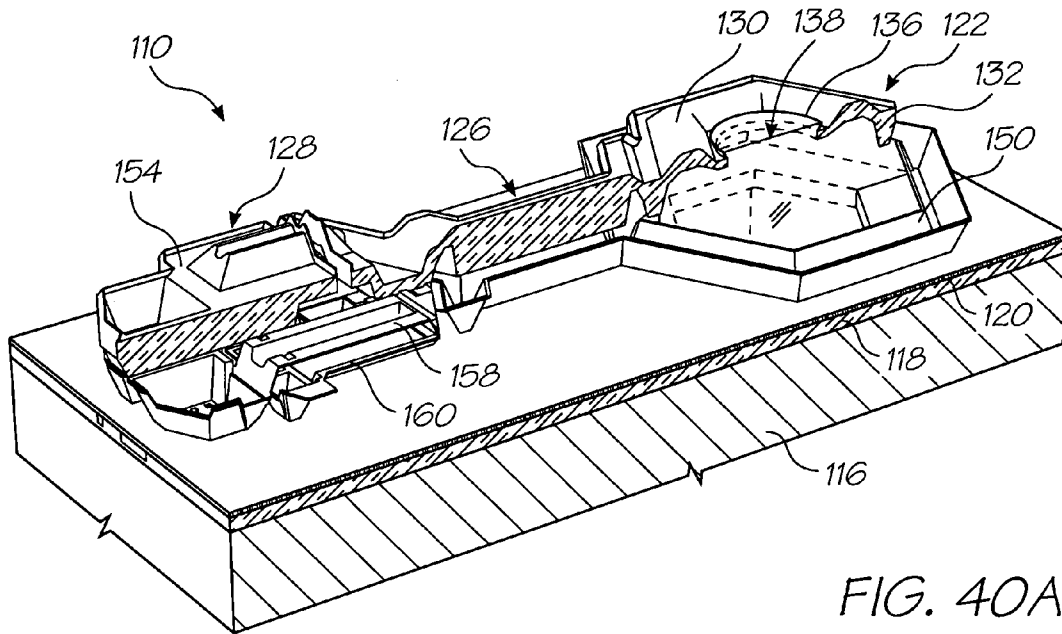


FIG. 38R



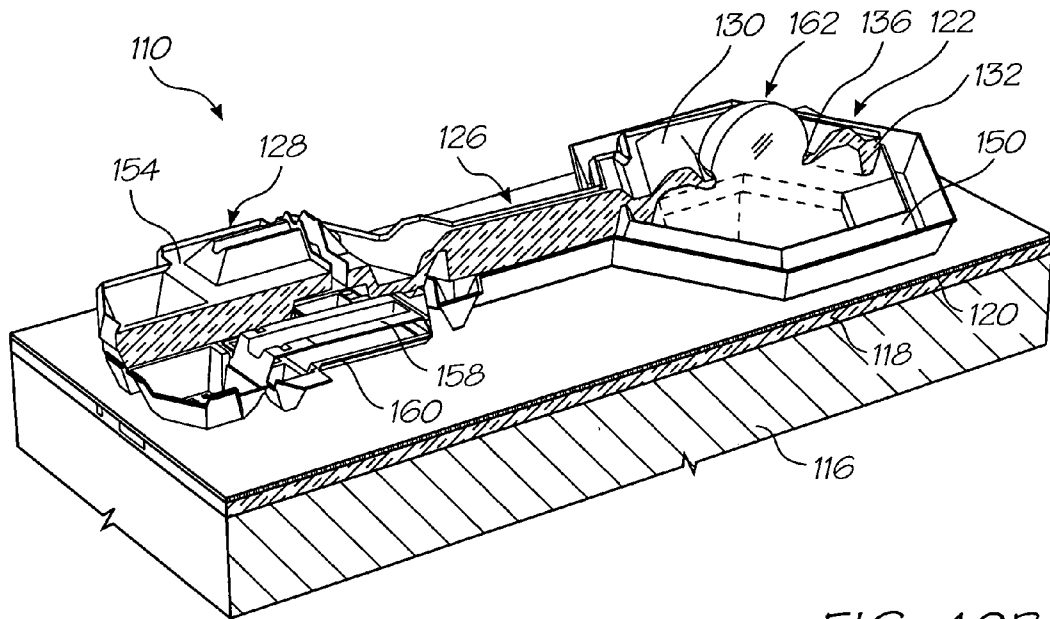


FIG. 40B

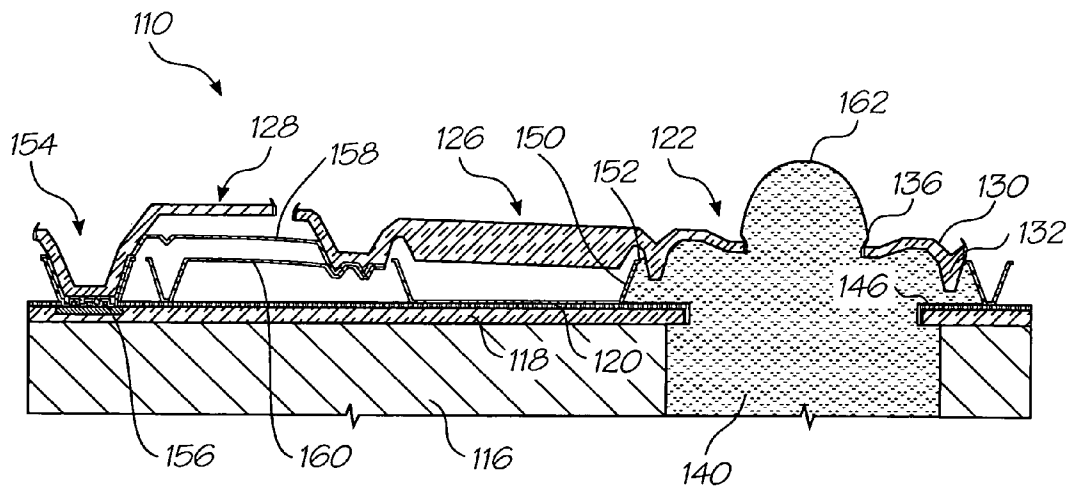


FIG. 41B

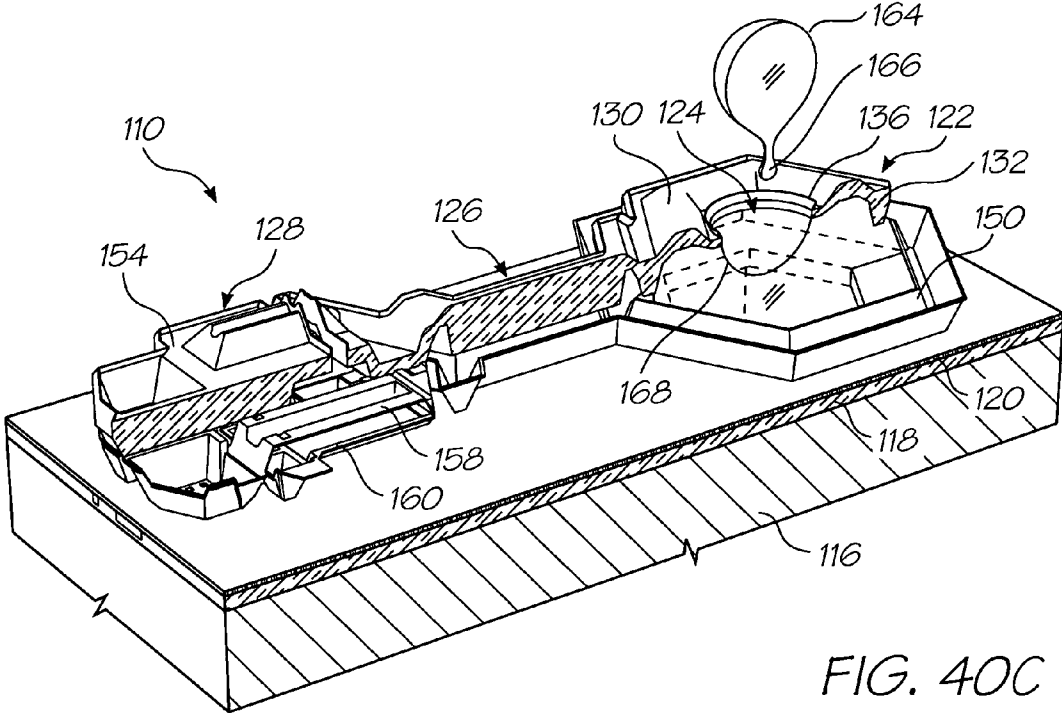


FIG. 40C

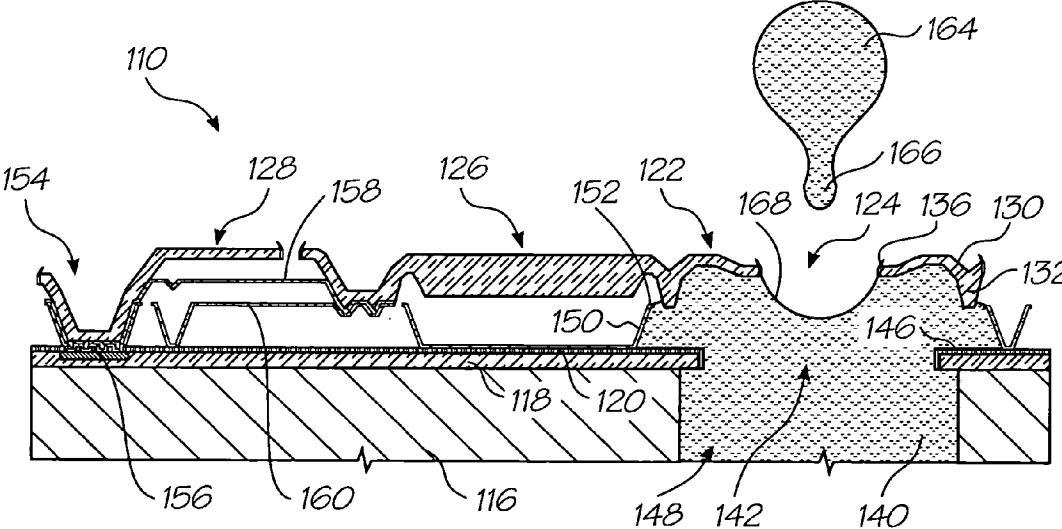


FIG. 41C

**MICRO-ELECTROMECHANICAL FLUID
EJECTION DEVICE HAVING A
BUCKLE-RESISTANT ACTUATOR**

CROSS-REFERENCE TO RELATED
APPLICATIONS

This is a Continuation application of Ser. No. 10/728,887 filed on Dec. 8, 2003, now U.S. Pat. No. 6,824,252, which is a continuation application of Ser. No. 10/309,080 filed on Dec. 4, 2002, now U.S. Pat. No. 6,682,176, which is a continuation-in-part of Ser. No. 09/113,122 filed on Jul. 10, 1998, now U.S. Pat. No. 6,557,977.

FIELD OF THE INVENTION

The present invention relates to micro-electromechanical fluid ejection devices.

BACKGROUND OF THE INVENTION

Many different types of printing have been invented, a large number of which are presently in use. The known forms of printers have a variety of methods for marking the print media with relevant marking media. Commonly used forms of printing include offset printing, laser printing and copying devices, dot matrix type impact printers, thermal paper printers, film recorders, thermal wax printers, dye sublimation printers and ink jet printers both of the drop on demand and continuous flow type. Each type of printer has its own advantages and problems when considering cost, speed, quality, reliability, simplicity of construction and operation etc.

In recent years, the field of ink jet printing, wherein each individual pixel of ink is derived from one or more ink nozzles has become increasingly popular primarily due to its inexpensive and versatile nature.

Many different techniques on ink jet printing have been invented. For a survey of the field, reference is made to an article by J Moore, "Non-Impact Printing: Introduction and Historical Perspective", Output Hard Copy Devices, Editors R Dubeck and S Sherr, pages 207-220 (1988).

Ink Jet printers themselves come in many different types. The utilisation of a continuous stream of ink in ink jet printing appears to date back to at least 1929 wherein U.S. Pat. No. 1,941,001 by Hansell discloses a simple form of continuous stream electro-static ink jet printing.

U.S. Pat. No. 3,596,275 by Sweet also discloses a process of continuous ink jet printing including the step wherein the ink jet stream is modulated by a high frequency electrostatic field so as to cause drop separation. This technique is still utilized by several manufacturers including Elmjet and Scitex (see also U.S. Pat. No. 3,373,437 by Sweet et al)

Piezoelectric ink jet printers are also one form of commonly utilized ink jet printing device. Piezoelectric systems are disclosed by Kyser et. al. in U.S. Pat. No. 3,946,398 (1970) which utilizes a diaphragm mode of operation, by Zolten in U.S. Pat. No. 3,683,212 (1970) which discloses a squeeze mode of operation of a piezoelectric crystal, by Stemme in U.S. Pat. No. 3,747,120 (1972) which discloses a bend mode of piezoelectric operation, Howkins in U.S. Pat. No. 4,459,601 which discloses a piezoelectric push mode actuation of the ink jet stream and by Fischbeck in U.S. Pat. No. 4,584,590 which discloses a shear mode type of piezoelectric transducer element.

Recently, thermal ink jet printing has become an extremely popular form of ink jet printing. The ink jet

printing techniques include those disclosed by Endo et al in GB 2007162 (1979) and by Vaught et al in U.S. Pat. No. 4,490,728. Both the aforementioned reference ink jet printing techniques rely upon the activation of an electrothermal actuator which results in the creation of a bubble in a constricted space, such as a nozzle, which thereby causes the ejection of ink from an aperture in communication with the confined space onto a relevant print media. Manufacturers such as Canon and Hewlett Packard manufacture printing devices utilizing the electrothermal actuator.

As can be seen from the foregoing, many different types of printing technologies are available. Ideally, a printing technology should have a number of desirable attributes. These include inexpensive construction and operation, high-speed operation, safe and continuous long-term operation etc. Each technology may have its own advantages and disadvantages in the areas of cost, speed, quality, reliability, power usage, simplicity of construction, operation, durability and consumables.

In the construction of any inkjet printing system, there are a considerable number of important factors which must be traded off against one another especially as large scale printheads are constructed, especially those of a pagewidth type. A number of these factors are outlined in the following paragraphs.

Firstly, inkjet printheads are normally constructed utilizing micro-electromechanical systems (MEMS) techniques. As such, they tend to rely upon the standard integrated circuit construction/fabrication techniques of depositing planar layers on a silicon wafer and etching certain portions of the planar layers. Within silicon circuit fabrication technology, certain techniques are better known than others. For example, the techniques associated with the creation of CMOS circuits are likely to be more readily used than those associated with the creation of exotic circuits including ferroelectrics, gallium arsenide etc. Hence, it is desirable, in any MEMS construction, to utilize well-proven semiconductor fabrication techniques that do not require the utilization of any "exotic" processes or materials. Of course, a certain degree of trade off will be undertaken in that if the use of the exotic material far outweighs its disadvantages then it may become desirable to utilize the material anyway.

With a large array of ink ejection nozzles, it is desirable to provide for a highly automated form of manufacturing which results in an inexpensive production of multiple printhead devices.

Preferably, the device constructed utilizes a low amount of energy in the ejection of ink. The utilization of a low amount of energy is particularly important when a large pagewidth fill color printhead is constructed having a large array of individual print ejection mechanisms with each ejection mechanism, in the worst case, being fired in a rapid sequence.

In the parent application, namely U.S. application Ser. No. 09/113,122 there is disclosed a printhead chip having a plurality of nozzle arrangements. These nozzle arrangements each include an actuator. The actuator has two pairs of actuating arms, each pair comprising an active actuating arm and a passive actuating arm. The active actuating arms are configured so that when heated upon receipt of an electrical signal, they deform and drive an ink displacement mechanism so that ink can be ejected from the respective nozzle chambers. The passive actuating arms serve to provide resilient flexibility and stability to the actuator.

The Applicant has found that it is desirable that the actuator has a certain configuration to avoid buckling of the actuator when the active actuating arms are deformed to

displace the actuator. While avoiding buckling, this configuration must also maintain efficiency of the actuator. This configuration is the subject of this invention.

SUMMARY OF THE INVENTION

According to a first aspect of the invention, there is provided a micro-electromechanical fluid ejection device that comprises

a substrate that defines a fluid inlet channel and incorporates a wafer and CMOS layers positioned on the wafer;

a nozzle chamber structure that is positioned on the substrate to define a nozzle chamber in fluid communication with the fluid inlet channel and a fluid ejection port in fluid communication with the nozzle chamber, the nozzle chamber structure incorporating a fluid ejecting member that is displaceable with respect to the substrate to act on fluid in the nozzle chamber to eject the fluid from the fluid ejection port; and

an elongate actuator arm connected at one end to the substrate and at an opposite end to the fluid ejecting member, and having an active beam assembly and a passive beam assembly spaced from and parallel to the active beam assembly, the beam assemblies being mechanically connected, but electrically isolated from each other, with the active beam assembly defining an electrical heating circuit connected to the CMOS layers and being capable of thermal expansion so that the arm experiences differential thermal expansion to be displaced with respect to the substrate thus displacing the fluid ejecting member, wherein

a spacing between the active beam assembly and the passive beam assembly is between one percent and twenty percent of a length of the actuator arm.

Said spacing may be between five percent and ten percent of the length of the actuator arm.

The fluid ejecting member may comprise a crown portion that defines the fluid ejection port and a skirt portion that depends from a periphery of the crown portion. The nozzle chamber structure may include a wall that bounds the inlet channel and overlaps the skirt portion so that displacement of the fluid ejecting member results in a change of volume of the nozzle chamber to eject fluid from the nozzle chamber.

The passive beam assembly may be interposed between the active beam assembly and the substrate so that thermal expansion of the active beam assembly causes the opposite end of the actuator to be displaced towards the substrate resulting in the fluid ejecting member reducing a volume of the nozzle chamber so that fluid is ejected from the fluid ejection port.

A connecting member may interconnect the opposite end of the actuator arm and the fluid ejecting member.

The wall that bounds the inlet channel may have an inwardly directed lip which, together with the skirt portion, provides an anchor point for a meniscus that defines a fluidic seal for preventing fluid leakage during operation.

The beam assemblies may both be substantially of titanium nitride.

According to a second aspect of the invention, there is provided a micro-electromechanical fluid ejection device that comprises

a substrate that defines a fluid inlet channel and incorporates a wafer and CMOS layers positioned on the wafer;

a nozzle chamber structure that is positioned on the substrate to define a nozzle chamber in fluid communication with the fluid inlet channel and a fluid ejection port in fluid communication with the nozzle chamber;

an actuator that is connected to the CMOS layers and operatively positioned with respect to the nozzle chamber, the actuator being displaceable on receipt of an electrical signal from the CMOS layers to act on fluid in the nozzle chamber to eject fluid from the fluid ejection port; and

a nozzle guard that is mounted on the substrate to be spaced from and cover the nozzle chamber structure, the nozzle guard including a body member that defines a passage that is aligned with the fluid ejection port so that fluid ejected from the fluid ejection port passes through the passage.

The nozzle guard may include support members that are fast with the substrate to support the body member above the nozzle chamber structure.

The support members may define air inlet openings to permit air to be pumped into a region between the nozzle chamber structure and the body member and to exit through the passage.

The actuator may be elongate and may be connected at one end to the CMOS layers. An opposite end of the actuator may be displaceable towards and away from the substrate on receipt of an electrical signal from the CMOS layers. The nozzle chamber structure may include a nozzle that is connected to said opposite end of the actuator. The nozzle may have a crown portion and a skirt portion that depends from the crown portion, the crown portion defining the fluid ejection port and the skirt portion being positioned so that the nozzle and the wall define the nozzle chamber. A volume of the nozzle chamber may thus be reduced and subsequently enlarged as the nozzle is driven towards and away from the nozzle chamber by the actuator to eject fluid from the fluid ejection port.

An edge of the skirt portion may be positioned adjacent an edge of the wall such that, when the nozzle chamber is filled with liquid, a meniscus is pinned by the edges of the skirt portion and the wall to define a fluidic seal that inhibits the egress of liquid from between the wall and the skirt as liquid is ejected from the fluid ejection port.

The crown portion may include a rim that defines the fluid ejection port. The rim may provide an anchor point for a meniscus that is formed in the fluid ejection port when the chamber is filled with liquid.

According to a third aspect of the invention, there is provided a micro-electromechanical fluid ejection device which comprises

a substrate that defines a plurality of fluid inlet channels and incorporates a wafer and CMOS layers positioned on the wafer;

nozzle chamber structures that are positioned on the substrate to define nozzle chambers in fluid communication with respective fluid inlet channels and fluid ejection ports in fluid communication with respective nozzle chambers;

actuators that are connected to the CMOS layers and operatively positioned with respect to respective nozzle chambers, the actuators being displaceable on receipt of an electrical signal from the CMOS layers to act on fluid in the respective nozzle chambers to eject fluid from the fluid ejection ports; and

a nozzle guard that is mounted on the substrate to be spaced from and cover the nozzle chamber structures, the nozzle guard including a body member that defines passages that are aligned with respective fluid ejection ports so that fluid ejected from the fluid ejection ports passes through the passages.

In general, there is disclosed herein an ink jet nozzle assembly including a nozzle chamber and a nozzle, the chamber including a movable portion and an actuating arm

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connected to or formed integrally with the movable portion and functioning in use to move said movable portion selectively to eject ink from the chamber via said nozzle, the actuating arm having portions with equivalent thermal expansion characteristics so as to avoid differential thermal expansion in response to changes in ambient temperature.

Preferably the actuating arm is formed of materials having equivalent thermal expansion characteristics and a current is passed through only a portion of the actuating arm to effect said movement.

Preferably said nozzle chamber has an inlet in fluid communication with an ink reservoir. The nozzle chamber may include a fixed portion configured with said movable portion such that relative movement in an ejection phase reduces an effective volume of the chamber, and alternate relative movement in a refill phase enlarges the effective volume of the chamber;

Portions of the actuating arms may be spaced apart and are adapted for selective differential thermal expansion upon heating so as to effect said relative movement.

The inlet may be positioned and dimensioned relative to the nozzle such that ink is ejected preferentially from the chamber through said nozzle in droplet form in the ejection phase, and ink is alternately drawn preferentially into the chamber from the reservoir through the inlet in the refill phase.

Preferably, said movable portion includes the nozzle and the fixed portion is mounted on a substrate.

Preferably the actuating arm effectively extends between the movable portion and the substrate.

Preferably the fixed portion includes the nozzle mounted on a substrate and the movable portion includes an ejection paddle.

Preferably the actuating arm is located substantially within the chamber.

Alternatively the actuating arm is located substantially outside the chamber.

Preferably the fixed portion includes a slotted sidewall in the chamber through which the actuating arm is connected to the movable portion.

Preferably the actuating arm has two portions that are of substantially the same cross-sectional profile relative to one another.

Alternatively the portions of the actuating arm are of different cross-sectional profiles relative to one another.

Preferably the portions are of substantially the same material composition relative to one another.

Alternatively the portions are of different material composition relative to one another.

Preferably the portions are substantially parallel to one another.

Alternatively the portions are substantially non-parallel to one another.

Preferably one portion is adapted to be heated to a higher temperature than the other portion in order to effect thermal actuation.

Preferably the respective portions are formed from multiple layers of different material compositions disposed such that thermal expansion or contraction in one portion due to the ambient temperature fluctuations is balanced by a substantially corresponding thermal expansion or contraction in the other portion.

Preferably the assembly is manufactured using micro-electro-mechanical-systems (MEMS) techniques.

Preferably an electric current is passed through one said portion arm and not the other said portion in use.

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According to a third aspect of the invention, there is provided an ink jet printhead chip that comprises

a substrate;

a plurality of nozzle arrangements positioned on the substrate, each nozzle arrangement comprising nozzle chamber walls that define a nozzle chamber and an ink ejection port in fluid communication with the nozzle chamber;

an actuator that is connected to the substrate and is displaceable with respect to the substrate upon receipt of a control signal, the actuator being operatively arranged with respect to the nozzle chamber to eject ink from the ink ejection port on displacement of the actuator; wherein

the actuator includes an actuating arm that has at least one active portion that is configured to be displaced upon receipt of the control signal and at least one corresponding passive portion, the, or each, active portion being spaced from its corresponding passive portion in a plane that spans the substrate, so that spacing between the, or each, active portion and its corresponding passive portion is greater than one percent of a length of the actuating arm and less than twenty percent of the length of the actuating arm.

The actuator may include at least two pairs of corresponding active and passive portions.

Each active portion may be in the form of an elongate active beam and each passive portion may be in the form of an elongate passive beam.

The spacing between each active beam and its associated passive beam may be greater than five percent of the length of the actuating arm and less than ten percent of the length of the actuating arm.

The actuator may include an ink ejecting mechanism that is operatively positioned with respect to the nozzle chamber. An end of the actuating arm may be anchored to the substrate and an opposed end of the actuating arm may be connected to the ink ejecting mechanism so that displacement of the actuating arm results in the ink ejecting mechanism ejecting ink from the ink ejection port.

The invention extends to an ink jet printhead, which comprises at least one ink jet printhead chip as described above.

BRIEF DESCRIPTION OF THE DRAWINGS

Notwithstanding any other forms, which may fall within the scope of the present invention, preferred forms of the invention will now be described, by way of example only, with reference to the accompanying drawings in which:

FIGS. 1-3 illustrate the operational principles of the preferred embodiment;

FIG. 4 is a side perspective view of a single nozzle arrangement of the preferred embodiment;

FIG. 5 illustrates a sectional side view of a single nozzle arrangement;

FIGS. 6 and 7 illustrate operational principles of the preferred embodiment;

FIGS. 8-15 illustrate the manufacturing steps in the construction of the preferred embodiment;

FIG. 16 illustrates a top plan view of a single nozzle;

FIG. 17 illustrates a portion of a single color printhead device;

FIG. 18 illustrates a portion of a three-color printhead device;

FIG. 19 provides a legend of the materials indicated in FIGS. 20 to 29;

FIG. 20 to FIG. 29 illustrate sectional views of the manufacturing steps in one form of construction of an ink jet printhead nozzle;

FIG. 30 shows a three dimensional, schematic view of a nozzle assembly for an ink jet printhead in accordance with another embodiment of the invention;

FIGS. 31 to 33 show a three dimensional, schematic illustration of an operation of the nozzle assembly of FIG. 30;

FIG. 34 shows a three dimensional view of a nozzle array constituting an ink jet printhead;

FIG. 35 shows, on an enlarged scale, part of the array of FIG. 34;

FIG. 36 shows a three dimensional view of an ink jet printhead including a nozzle guard;

FIGS. 37a to 37r show three-dimensional views of steps in the manufacture of a nozzle assembly of an ink jet printhead;

FIGS. 38a to 38r show sectional side views of the manufacturing steps;

FIGS. 39a to 39k show layouts of masks used in various steps in the manufacturing process;

FIGS. 40a to 40c show three dimensional views of an operation of the nozzle assembly manufactured according to the method of FIGS. 37 and 38; and

FIGS. 41a to 41c show sectional side views of an operation of the nozzle assembly manufactured according to the method of FIGS. 37 and 38.

DESCRIPTION OF PREFERRED AND OTHER EMBODIMENTS

In the preferred embodiment, there is provided a nozzle chamber having ink within it and a thermal actuator device interconnected to an ink ejecting mechanism in the form of a paddle, the thermal actuator device being actuated so as to eject ink from the nozzle chamber. The preferred embodiment includes a particular thermal actuator structure which includes an actuator arm in the form of a tapered heater structure arm for providing positional heating of a conductive heater layer row. The actuator arm is connected to the paddle through a slotted wall in the nozzle chamber. The actuator arm has a mating shape so as to mate substantially with the surfaces of the slot in the nozzle chamber wall.

Turning initially to FIGS. 1-3, there is provided schematic illustrations of the basic operation of the device. A nozzle chamber 1 is provided filled with ink 2 by means of an ink inlet channel 3 which can be etched through a wafer substrate on which the nozzle chamber 1 rests. The nozzle chamber 1 includes an ink ejection nozzle or aperture 4 around which an ink meniscus forms.

Inside the nozzle chamber 1 is a paddle type device 7 which is connected to an actuator arm 8 through a slot in the wall of the nozzle chamber 1. The actuator arm 8 includes a heater means 9 located adjacent to a post end portion 10 of the actuator arm. The post 10 is fixed to a substrate.

When it is desired to eject a drop from the nozzle chamber, as illustrated in FIG. 2, the heater means 9 is heated so as to undergo thermal expansion. Preferably, the heater means itself or the other portions of the actuator arm 8 are built from materials having a high bend efficiency where the bend efficiency is defined as

$$\text{band efficiency} = \frac{\text{Young's Modulus} \times (\text{Coefficient of thermal Expansion})}{\text{Density} \times \text{Specific Heat Capacity}}$$

A suitable material for the heater elements is a copper nickel alloy which can be formed so as to bend a glass material.

The heater means is ideally located adjacent the post end portion 10 such that the effects of activation are magnified at the paddle end 7 such that small thermal expansions near post 10 result in large movements of the paddle end. The heating 9 causes a general increase in pressure around the ink meniscus 5 which expands, as illustrated in FIG. 2, in a rapid manner. The heater current is pulsed and ink is ejected out of the nozzle 4 in addition to flowing in from the ink channel 3. Subsequently, the paddle 7 is deactivated to again return to its quiescent position. The deactivation causes a general reflux of the ink into the nozzle chamber. The forward momentum of the ink outside the nozzle rim and the corresponding backflow results in a general necking and breaking off of a drop 12 which proceeds to the print media. The collapsed meniscus 5 results in a general sucking of ink into the nozzle chamber 1 via the in flow channel 3. In time, the nozzle chamber is refilled such that the position in FIG. 1 is again reached and the nozzle chamber is subsequently ready for the ejection of another drop of ink.

Turning now to FIG. 4, there is illustrated a single nozzle arrangement 20 of the preferred embodiment. The arrangement includes an actuator arm 21 which includes a bottom layer 22 which is constructed from a conductive material such as a copper nickel alloy (hereinafter called cupronickel) or titanium nitride (TiN). The layer 22, as will become more apparent hereinafter includes a tapered end portion near the end post 24. The tapering of the layer 22 near this end means that any conductive resistive heating occurs near the post portion 24.

The layer 22 is connected to the lower CMOS layers 26 which are formed in the standard manner on a silicon substrate surface 27. The actuator arm 21 is connected to an ejection paddle which is located within a nozzle chamber 28. The nozzle chamber 28 includes an ink ejection nozzle 29 from which ink is ejected and includes a convoluted slot arrangement 30 which is constructed such that the actuator arm 21 is able to move up and down while causing minimal pressure fluctuations in the area of the nozzle chamber 28 around the slot 30.

FIG. 5 illustrates a sectional view through a single nozzle. FIG. 5 illustrates more clearly the internal structure of the nozzle chamber which includes the paddle 32 attached to the actuator arm 21 having face 33. Importantly, the actuator arm 21 includes, as noted previously, a bottom conductive layer 22. Additionally, a top layer 25 is also provided.

The utilization of a second layer 25 of the same material as the first layer 22 allows for more accurate control of the actuator position as will be described with reference to FIGS. 6 and 7. In FIG. 6, there is illustrated the example where a high Young's Modulus material 40 is deposited utilizing standard semiconductor deposition techniques and on top of which is further deposited a second layer 41 having a much lower Young's Modulus. Unfortunately, the deposition is likely to occur at a high temperature. Upon cooling, the two layers are likely to have different coefficients of thermal expansion and different Young's Moduli. Hence, in ambient room temperature, the thermal stresses are likely to cause bending of the two layers of material as shown at 42.

By utilizing a second deposition of the material having a high Young's Modulus, the situation in FIG. 7 is likely to result wherein the material 41 is sandwiched between the two layers 40. Upon cooling, the two layers 40 are kept in tension with one another so as to result in a more planar structure 45 regardless of the operating temperature. This principle is utilized in the deposition of the two layers 22, 25 of FIGS. 4-5.

Turning again to FIGS. 4 and 5, one important attribute of the preferred embodiments includes the slotted arrangement 30. The slotted arrangement results in the actuator arm 21 moving up and down thereby causing the paddle 32 to also move up and down resulting in the ejection of ink. The slotted arrangement 30 results in minimum ink outflow through the actuator arm connection and also results in minimal pressure increases in this area. The face 33 of the actuator arm is extended out so as to form an extended interconnect with the paddle surface thereby providing for better attachment. The face 33 is connected to a block portion 36 which is provided to provide a high degree of rigidity. The actuator arm 21 and the wall of the nozzle chamber 28 have a generally corrugated nature so as to reduce any flow of ink through the slot 30. The exterior surface of the nozzle chamber adjacent the block portion 36 has a rim eg. 38 so to minimize wicking of ink outside of the nozzle chamber. A pit 37 is also provided for this purpose. The pit 37 is formed in the lower CMOS layers 26. An ink supply channel 39 is provided by means of back etching through the wafer to the back surface of the nozzle.

Turning to FIGS. 8-15 there will now be described fabrication steps utilized in the construction of a single nozzle in accordance with the preferred embodiment.

The fabrication uses standard micro-electromechanical techniques. For a general introduction to a micro-electromechanical systems (MEMS) reference is made to standard proceedings in this field including the proceeding of the SPIE (International Society for Optical Engineering) including volumes 2642 and 2882 which contain the proceedings of recent advances and conferences in this field.

1. The preferred embodiment starts with a double sided polished wafer complete with, say, a 0.2 μm 1 poly 2 metal CMOS process providing for all the electrical interconnects necessary to drive the inkjet nozzle.

2. As shown in FIG. 8, the CMOS wafer 26 is etched at 50 down to the silicon layer 27. The etching includes etching down to an aluminum CMOS layer 51, 52.

3. Next, as illustrated in FIG. 9, a 1 μm layer of sacrificial material 55 is deposited. The sacrificial material can be aluminum or photosensitive polyimide.

4. The sacrificial material is etched in the case of aluminum or exposed and developed in the case of polyimide in the area of the nozzle rim 56 and including a dishd paddle area 57.

5. Next, a 1 μm layer of heater material 60 (cupronickel or TiN) is deposited.

6. A 3.4 μm layer of PECVD glass 61 is then deposited.

7. A second layer 62 equivalent to the first layer 60 is then deposited.

8. All three layers 60-62 are then etched utilizing the same mask. The utilization of a single mask substantially reduces the complexity in the processing steps involved in creation of the actuator paddle structure and the resulting structure is as illustrated in FIG. 10. Importantly, a break 63 is provided so as to ensure electrical isolation of the heater portion from the paddle portion.

9. Next, as illustrated in FIG. 11, a 10 μm layer of sacrificial material 70 is deposited.

10. The deposited layer is etched (or just developed if polyimide) utilizing a fourth mask which includes nozzle rim etchant holes 71, block portion holes 72 and post portion 73.

11. Next a 10 μm layer of PECVD glass is deposited so as to form the nozzle rim 71, arm portions 72 and post portions 73.

12. The glass layer is then planarized utilizing chemical mechanical planarization (CMP) with the resulting structure as illustrated in FIG. 11.

13. Next, a 3 μm layer of PECVD glass is deposited.

14. The deposited glass is then etched as shown in FIG. 12, to a depth of approximately 1 μm so as to form nozzle rim portion 81 and actuator interconnect portion 82.

15. Next, as illustrated in FIG. 13, the glass layer is etched utilizing a 6th mask so as to form final nozzle rim portion 81 and actuator guide portion 82.

16. Next, as illustrated in FIG. 14, the ink supply channel is back etched 85 from the back of the wafer utilizing a 7th mask. The etch can be performed utilizing a high precision deep silicon trench etcher such as the STS Advanced Silicon Etcher (ASE). This step can also be utilized to nearly completely dice the wafer.

17. Next, as illustrated in FIG. 15 the sacrificial material can be stripped or dissolved to also complete dicing of the wafer in accordance with requirements.

18. Next, the printheads can be individually mounted on attached molded plastic ink channels to supply ink to the ink supply channels.

19. The electrical control circuitry and power supply can then be bonded to an etch of the printhead with a TAB film.

20. Generally, if necessary, the surface of the printhead is then hydrophobized so as to ensure minimal wicking of the ink along external surfaces. Subsequent testing can determine operational characteristics.

Importantly, as shown in the plan view of FIG. 16, the heater element has a tapered portion adjacent the post 73 so as to ensure maximum heating occurs near the post.

Of course, different forms of inkjet printhead structures can be formed. For example, there is illustrated in FIG. 17, a portion of a single color printhead having two spaced apart rows 90, 91, with the two rows being interleaved so as to provide for a complete line of ink to be ejected in two stages. Preferably, a guide rail 92 is provided for proper alignment of a TAB film with bond pads 93. A second protective barrier 94 can also preferably be provided. Preferably, as will become more apparent with reference to the description of FIG. 18 adjacent actuator arms are interleaved and reversed.

Turning now to FIG. 18, there is illustrated a full color printhead arrangement which includes three series of inkjet nozzles 95, 96, 97 one each devoted to a separate color. Again, guide rails 98, 99 are provided in addition to bond pads, eg. 100. In FIG. 18, there is illustrated a general plan of the layout of a portion of a full color printhead which clearly illustrates the interleaved nature of the actuator arms.

The presently disclosed ink jet printing technology is potentially suited to a wide range of printing system including: color and monochrome office printers, short run digital printers, high speed digital printers, offset press supplemental printers, low cost scanning printers high speed pagewidth printers, notebook computers with inbuilt pagewidth printers, portable color and monochrome printers, color and monochrome copiers, color and monochrome facsimile machines, combined printer, facsimile and copying machines, label printers, large format plotters, photograph copiers, printers for digital photographic "minilabs", video printers, PHOTO CD (PHOTO CD is a registered trademark

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of the Eastman Kodak Company) printers, portable printers for PDAs, wallpaper printers, indoor sign printers, billboard printers, fabric printers, camera printers and fault tolerant commercial printer arrays.

One alternative form of detailed manufacturing process which can be used to fabricate monolithic ink jet printheads operating in accordance with the principles taught by the present embodiment can proceed utilizing the following steps:

1. Using a double sided polished wafer **27**, complete drive transistors, data distribution, and timing circuits using a 0.5 micron, one poly, 2 metal CMOS process to form layer **26**. Relevant features of the wafer at this step are shown in FIG. **20**. For clarity, these diagrams may not be to scale, and may not represent a cross section though any single plane of the nozzle. FIG. **19** is a key to representations of various materials in these manufacturing diagrams, and those of other cross-referenced inkjet configurations.

2. Etch oxide down to silicon or aluminum using Mask **1**. This mask defines the nozzle chamber, the surface anti-wicking notch **37**, and the heater contacts **110**. This step is shown in FIG. **21**.

3. Deposit 1 micron of sacrificial material **55** (e.g. aluminum or photosensitive polyimide)

4. Etch (if aluminum) or develop (if photosensitive polyimide) the sacrificial layer using Mask **2**. This mask defines the nozzle chamber walls **112** and the actuator anchor point. This step is shown in FIG. **22**.

5. Deposit 1 micron of heater material **60** (e.g. cupronickel or TiN). If cupronickel, then deposition can consist of three steps—a thin anti-corrosion layer of, for example, TiN, followed by a seed layer, followed by electroplating of the 1 micron of cupronickel.

6. Deposit 3.4 microns of PECVD glass **61**.

7. Deposit a layer **62** identical to step 5.

8. Etch both layers of heater material, and glass layer, using Mask **3**. This mask defines the actuator, paddle, and nozzle chamber walls. This step is shown in FIG. **23**.

9. Wafer probe. All electrical connections are complete at this point, bond pads are accessible, and the chips are not yet separated.

10. Deposit 10 microns of sacrificial material **70**.

11. Etch or develop sacrificial material using Mask **4**. This mask defines the nozzle chamber wall **112**. This step is shown in FIG. **24**.

12. Deposit 3 microns of PECVD glass **113**.

13. Etch to a depth of (approx.) 1 micron using Mask **5**. This mask defines the nozzle rim **81**. This step is shown in FIG. **25**.

14. Etch down to the sacrificial layer using Mask **6**. This mask defines the roof **114** of the nozzle chamber, and the nozzle itself. This step is shown in FIG. **26**.

15. Back-etch completely through the silicon wafer (with, for example, an ASE Advanced Silicon Etcher from Surface Technology Systems) using Mask **7**. This mask defines the ink inlets **30** which are etched through the wafer. The wafer is also diced by this etch. This step is shown in FIG. **27**.

16. Etch the sacrificial material. The nozzle chambers are cleared, the actuators freed, and the chips are separated by this etch. This step is shown in FIG. **28**.

17. Mount the printheads in their packaging, which may be a molded plastic former incorporating ink channels which supply the appropriate color ink to the ink inlets at the back of the wafer.

18. Connect the printheads to their interconnect systems. For a low profile connection with minimum disruption of

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airflow, TAB may be used. Wire bonding may also be used if the printer is to be operated with sufficient clearance to the paper.

19. Hydrophobize the front surface of the printheads.

20. Fill the completed printheads with ink **115** and test them. A filled nozzle is shown in FIG. **29**.

Referring now to FIG. **30** of the drawings, a nozzle assembly, in accordance with a further embodiment of the invention is designated generally by the reference numeral **110**. An ink jet printhead has a plurality of nozzle assemblies **110** arranged in an array **114** (FIGS. **34** and **35**) on a silicon substrate **116**. The array **114** will be described in greater detail below.

The assembly **110** includes a silicon substrate or wafer **116** on which a dielectric layer **118** is deposited. A CMOS passivation layer **120** is deposited on the dielectric layer **118**.

Each nozzle assembly **110** includes a nozzle **122** defining a nozzle opening **124**, a connecting member in the form of a lever arm **126** and an actuator **128**. The lever arm **126** connects the actuator **128** to the nozzle **122**.

As shown in greater detail in FIGS. **31** to **33** of the drawings, the nozzle **122** comprises a crown portion **130** with a skirt portion **132** depending from the crown portion **130**. The skirt portion **132** forms part of a peripheral wall of a nozzle chamber **134** (FIGS. **31** to **33** of the drawings). The nozzle opening **124** is in fluid communication with the nozzle chamber **134**. It is to be noted that the nozzle opening **124** is surrounded by a raised rim **136** which "pins" a meniscus **138** (FIG. **31**) of a body of ink **140** in the nozzle chamber **134**.

An ink inlet aperture **142** (shown most clearly in FIG. **35** of the drawing) is defined in a floor **146** of the nozzle chamber **134**. The aperture **142** is in fluid communication with an ink inlet channel **148** defined through the substrate **116**.

A wall portion **150** bounds the aperture **142** and extends upwardly from the floor portion **146**. The skirt portion **132**, as indicated above, of the nozzle **122** defines a first part of a peripheral wall of the nozzle chamber **134** and the wall portion **150** defines a second part of the peripheral wall of the nozzle chamber **134**.

The wall **150** has an inwardly directed lip **152** at its free end which serves as a fluidic seal which inhibits the escape of ink when the nozzle **122** is displaced, as will be described in greater detail below. It will be appreciated that, due to the viscosity of the ink **140** and the small dimensions of the spacing between the lip **152** and the skirt portion **132**, the inwardly directed lip **152** and surface tension function as a seal for inhibiting the escape of ink from the nozzle chamber **134**.

The actuator **128** is a thermal bend actuator and is connected to an anchor **154** extending upwardly from the substrate **116** or, more particularly, from the CMOS passivation layer **120**. The anchor **154** is mounted on conductive pads **156** which form an electrical connection with the actuator **128**.

The actuator **128** comprises an actuator arm in the form of a pair of active beams **158** arranged above a pair of passive beams **160**. In a preferred embodiment, both beams **158** and **160** are of, or include, a conductive ceramic material such as titanium nitride (TiN).

The beams **158** and **160** have their first ends anchored to the anchor **154** and their opposed ends connected to the arm **126**. When a current is caused to flow through the active beams **158** thermal expansion of the beams **158** results. As the passive beams **160**, through which there is no current flow, do not expand at the same rate, a bending moment is

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created causing the arm **126** and, hence, the nozzle **122** to be displaced downwardly towards the substrate **116** as shown in FIG. **32** of the drawings. This causes an ejection of ink through the nozzle opening **124** as shown at **162** in FIG. **32** of the drawings. Thus, the nozzle **122** and the arm **126** define an ink ejecting mechanism. When the source of heat is removed from the active beams **158**, i.e. by stopping current flow, the nozzle **122** returns to its quiescent position as shown in FIG. **33** of the drawings. When the nozzle **122** returns to its quiescent position, an ink droplet **164** is formed as a result of the breaking of an ink droplet neck as illustrated at **166** in FIG. **33** of the drawings. The ink droplet **164** then travels on to the print media such as a sheet of paper. As a result of the formation of the ink droplet **164**, a “negative” meniscus is formed as shown at **168** in FIG. **33** of the drawings. This “negative” meniscus **168** results in an inflow of ink **140** into the nozzle chamber **134** such that a new meniscus **138** (FIG. **31**) is formed in readiness for the next ink drop ejection from the nozzle assembly **110**.

Each active beam **158** corresponds with one passive beam **160** to form two pairs of beams comprising an active beam **158** and a corresponding passive beam **160**. Each active beam **158** is spaced from its corresponding passive beam **160** in a plane that is substantially parallel to the substrate. The spacing between each active beam **158** and its respective passive beam **160** is suitably between 1 percent and 20 percent of the length of the beams. Preferably the spacing is between 5 percent and 10 percent of the length of the beams. The Applicant has found that this configuration provides the best protection against mutual buckling while maintaining efficiency of operation. In particular, Applicant has found that if the spacing is less than 1 percent of the length of the beams there is an unacceptable risk of mutual buckling and if the spacing is greater than 20 percent of the length of the beams the efficiency of the actuators **128** is compromised.

Referring now to FIGS. **34** and **35** of the drawings, the nozzle array **114** is described in greater detail. The array **114** is for a four-color printhead. Accordingly, the array **114** includes four groups **170** of nozzle assemblies, one for each color. Each group **170** has its nozzle assemblies **110** arranged in two rows **172** and **174**. One of the groups **170** is shown in greater detail in FIG. **35** of the drawings.

To facilitate close packing of the nozzle assemblies **110** in the rows **172** and **174**, the nozzle assemblies **110** in the row **174** are offset or staggered with respect to the nozzle assemblies **110** in the row **172**. Also, the nozzle assemblies **110** in the row **172** are spaced apart sufficiently far from each other to enable the lever arms **126** of the nozzle assemblies **110** in the row **174** to pass between adjacent nozzles **122** of the assemblies **110** in the row **172**. It is to be noted that each nozzle assembly **110** is substantially dumbbell shaped so that the nozzles **122** in the row **172** nest between the nozzles **122** and the actuators **128** of adjacent nozzle assemblies **110** in the row **174**.

Further, to facilitate close packing of the nozzles **122** in the rows **172** and **174**, each nozzle **122** is substantially hexagonally shaped.

It will be appreciated by those skilled in the art that, when the nozzles **122** are displaced towards the substrate **116**, in use, due to the nozzle opening **124** being at a slight angle with respect to the nozzle chamber **134** ink is ejected slightly off the perpendicular. It is an advantage of the arrangement shown in FIGS. **34** and **35** of the drawings that the actuators **128** of the nozzle assemblies **110** in the rows **172** and **174** extend in the same direction to one side of the rows **172** and **174**. Hence, the ink droplets ejected from the nozzles **122** in

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the row **172** and the ink droplets ejected from the nozzles **122** in the row **174** are parallel to one another resulting in an improved print quality.

Also, as shown in FIG. **34** of the drawings, the substrate **116** has bond pads **176** arranged thereon which provide the electrical connections, via the pads **156**, to the actuators **128** of the nozzle assemblies **110**. These electrical connections are formed via the CMOS layer (not shown).

Referring to FIG. **36** of the drawings, a development of the invention is shown. With reference to the previous drawings, like reference numerals refer to like parts, unless otherwise specified.

In this development, a nozzle guard **180** is mounted on the substrate **116** of the array **114**. The nozzle guard **180** includes a body member **182** having a plurality of passages **184** defined therethrough. The passages **184** are in register with the nozzle openings **124** of the nozzle assemblies **110** of the array **114** such that, when ink is ejected from any one of the nozzle openings **124**, the ink passes through the associated passage **184** before striking the print media.

The body member **182** is mounted in spaced relationship relative to the nozzle assemblies **110** by limbs or struts **186**. One of the struts **186** has air inlet openings **188** defined therein.

In use, when the array **114** is in operation, air is charged through the inlet openings **188** to be forced through the passages **184** together with ink travelling through the passages **184**.

The ink is not entrained in the air as the air is charged through the passages **184** at a different velocity from that of the ink droplets **164**. For example, the ink droplets **164** are ejected from the nozzles **122** at a velocity of approximately 3 m/s. The air is charged through the passages **184** at a velocity of approximately 1 m/s.

The purpose of the air is to maintain the passages **184** clear of foreign particles. A danger exists that these foreign particles, such as dust particles, could fall onto the nozzle assemblies **110** adversely affecting their operation. With the provision of the air inlet openings **88** in the nozzle guard **180** this problem is, to a large extent, obviated.

Referring now to FIGS. **37** to **39** of the drawings, a process for manufacturing the nozzle assemblies **110** is described.

Starting with the silicon substrate or wafer **116**, the dielectric layer **118** is deposited on a surface of the wafer **116**. The dielectric layer **118** is in the form of approximately 1.5 microns of CVD oxide. Resist is spun on to the layer **118** and the layer **118** is exposed to mask **200** and is subsequently developed.

After being developed, the layer **118** is plasma etched down to the silicon layer **116**. The resist is then stripped and the layer **118** is cleaned. This step defines the ink inlet aperture **142**.

In FIG. **37b** of the drawings, approximately 0.8 microns of aluminum **202** is deposited on the layer **118**. Resist is spun on and the aluminum **202** is exposed to mask **204** and developed. The aluminum **202** is plasma etched down to the oxide layer **118**, the resist is stripped and the device is cleaned. This step provides the bond pads and interconnects to the ink jet actuator **128**. This interconnect is to an NMOS drive transistor and a power plane with connections made in the CMOS layer (not shown).

Approximately 0.5 microns of PECVD nitride is deposited as the CMOS passivation layer **120**. Resist is spun on and the layer **120** is exposed to mask **206** whereafter it is developed. After development, the nitride is plasma etched

down to the aluminum layer **202** and the silicon layer **116** in the region of the inlet aperture **142**. The resist is stripped and the device cleaned.

A layer **208** of a sacrificial material is spun on to the layer **120**. The layer **208** is 6 microns of photo-sensitive polyimide or approximately 4 μm of high temperature resist. The layer **208** is softbaked and is then exposed to mask **210** whereafter it is developed. The layer **208** is then hardbaked at 400° C. for one hour where the layer **208** is comprised of polyimide or at greater than 300° C. where the layer **208** is high temperature resist. It is to be noted in the drawings that the pattern-dependent distortion of the polyimide layer **208** caused by shrinkage is taken into account in the design of the mask **210**.

In the next step, shown in FIG. **37e** of the drawings, a second sacrificial layer **212** is applied. The layer **212** is either 2 μm of photosensitive polyimide, which is spun on, or approximately 1.3 μm of high temperature resist. The layer **212** is softbaked and exposed to mask **214**. After exposure to the mask **214**, the layer **212** is developed. In the case of the layer **212** being polyimide, the layer **212** is hardbaked at 400° C. for approximately one hour. Where the layer **212** is resist, it is hardbaked at greater than 300° C. for approximately one hour.

A 0.2 micron multi-layer metal layer **216** is then deposited. Part of this layer **216** forms the passive beam **160** of the actuator **128**.

The layer **216** is formed by sputtering 1,000 Å of titanium nitride (TiN) at around 300° C. followed by sputtering 50 Å of tantalum nitride (TaN). A further 1,000 Å of TiN is sputtered on followed by 50 Å of TaN and a further 1,000 Å of TiN.

Other materials which can be used instead of TiN are TiB₂, MoSi₂ or (Ti, Al)N.

The layer **216** is then exposed to mask **218**, developed and plasma etched down to the layer **212** whereafter resist, applied for the layer **216**, is wet stripped taking care not to remove the cured layers **208** or **212**.

A third sacrificial layer **220** is applied by spinning on 4 μm of photosensitive polyimide or approximately 2.6 μm high temperature resist. The layer **220** is softbaked whereafter it is exposed to mask **222**. The exposed layer is then developed followed by hardbaking. In the case of polyimide, the layer **220** is hardbaked at 400° C. for approximately one hour or at greater than 300° C. where the layer **220** comprises resist.

A second multi-layer metal layer **224** is applied to the layer **220**. The constituents of the layer **224** are the same as the layer **216** and are applied in the same manner. It will be appreciated that both layers **216** and **224** are electrically conductive layers.

The layer **224** is exposed to mask **226** and is then developed. The layer **224** is plasma etched down to the polyimide or resist layer **220** whereafter resist applied for the layer **224** is wet stripped taking care not to remove the cured layers **208**, **212** or **220**. It will be noted that the remaining part of the layer **224** defines the active beam **158** of the actuator **128**.

A fourth sacrificial layer **228** is applied by spinning on 4 μm of photosensitive polyimide or approximately 2.6 μm of high temperature resist. The layer **228** is softbaked; exposed to the mask **230** and is then developed to leave the island portions as shown in FIG. **9k** of the drawings. The remaining portions of the layer **228** are hardbaked at 400° C. for approximately one hour in the case of polyimide or at greater than 300° C. for resist.

As shown in FIG. **37l** of the drawing a high Young's modulus dielectric layer **232** is deposited. The layer **232** is

constituted by approximately 1 μm of silicon nitride or aluminum oxide. The layer **232** is deposited at a temperature below the hardbaked temperature of the sacrificial layers **208**, **212**, **220**, **228**. The primary characteristics required for this dielectric layer **232** are a high elastic modulus, chemical inertness and good adhesion to TiN.

A fifth sacrificial layer **234** is applied by spinning on 2 μm of photosensitive polyimide or approximately 1.3 μm of high temperature resist. The layer **234** is softbaked, exposed to mask **236** and developed. The remaining portion of the layer **234** is then hardbaked at 400° C. for one hour in the case of the polyimide or at greater than 300° C. for the resist.

The dielectric layer **232** is plasma etched down to the sacrificial layer **228** taking care not to remove any of the sacrificial layer **234**.

This step defines the nozzle opening **124**, the lever arm **126** and the anchor **154** of the nozzle assembly **110**.

A high Young's modulus dielectric layer **238** is deposited. This layer **238** is formed by depositing 0.2 μm of silicon nitride or aluminum nitride at a temperature below the hardbaked temperature of the sacrificial layers **208**, **212**, **220** and **228**.

Then, as shown in FIG. **37p** of the drawings, the layer **238** is anisotropically plasma etched to a depth of 0.35 microns. This etch is intended to clear the dielectric from the entire surface except the side walls of the dielectric layer **232** and the sacrificial layer **234**. This step creates the nozzle rim **136** around the nozzle opening **124** which "pins" the meniscus of ink, as described above.

An ultraviolet (UV) release tape **240** is applied. 4 μm of resist is spun on to a rear of the silicon wafer **116**. The wafer **116** is exposed to mask **242** to back etch the wafer **116** to define the ink inlet channel **148**. The resist is then stripped from the wafer **116**.

A further UV release tape (not shown) is applied to a rear of the wafer **16** and the tape **240** is removed. The sacrificial layers **208**, **212**, **220**, **228** and **234** are stripped in oxygen plasma to provide the final nozzle assembly **110** as shown in FIGS. **37r** and **38r** of the drawings. For ease of reference, the reference numerals illustrated in these two drawings are the same as those in FIG. **30** of the drawings to indicate the relevant parts of the nozzle assembly **110**. FIGS. **40** and **41** show the operation of the nozzle assembly **110**, manufactured in accordance with the process described above with reference to FIGS. **37** and **38**, and these figures correspond to FIGS. **31** to **34** of the drawings.

It would be appreciated by a person skilled in the art that numerous variations and/or modifications may be made to the present invention as shown in the specific embodiments without departing from the spirit or scope of the invention as broadly described. The present embodiments are, therefore, to be considered in all respects to be illustrative and not restrictive.

We claim:

1. A micro-electromechanical fluid ejection device that comprises

a substrate that defines a fluid inlet channel and incorporates a wafer and CMOS layers positioned on the wafer;

a nozzle chamber structure that is positioned on the substrate to define a nozzle chamber in fluid communication with the fluid inlet channel and a fluid ejection port in fluid communication with the nozzle chamber, the nozzle chamber structure incorporating a fluid ejecting member that is displaceable with respect to the substrate to act on fluid in the nozzle chamber to eject the fluid from the fluid ejection port; and

an elongate actuator arm connected at one end to the substrate and at an opposite end to the fluid ejecting member, and having an active beam assembly and a passive beam assembly spaced from and parallel to the active beam assembly, the beam assemblies being mechanically connected, but electrically isolated from each other, with the active beam assembly defining an electrical heating circuit connected to the CMOS layers and being capable of thermal expansion so that the arm experiences differential thermal expansion to be displaced with respect to the substrate thus displacing the fluid ejecting member, wherein

a spacing between the active beam assembly and the passive beam assembly is between one percent and twenty percent of a length of the actuator arm.

2. A micro-electromechanical fluid ejection device as claimed in claim 1, in which said spacing is between five percent and ten percent of the length of the actuator arm.

3. A micro-electromechanical fluid ejection device as claimed in claim 1, in which the fluid ejecting member comprises a crown portion that defines the fluid ejection port and a skirt portion that depends from a periphery of the crown portion, the nozzle chamber structure including a wall that bounds the inlet channel and overlaps the skirt portion so that displacement of the fluid ejecting member results in

a change of volume of the nozzle chamber to eject fluid from the nozzle chamber.

4. A micro-electromechanical fluid ejection device as claimed in claim 3, in which the passive beam assembly is interposed between the active beam assembly and the substrate so that thermal expansion of the active beam assembly causes the opposite end of the actuator to be displaced towards the substrate resulting in the fluid ejecting member reducing a volume of the nozzle chamber so that fluid is ejected from the fluid ejection port.

5. A micro-electromechanical fluid ejection device as claimed in claim 3, in which a connecting member interconnects the opposite end of the actuator arm and the fluid ejecting member.

6. A micro-electromechanical fluid ejection device as claimed in claim 3, in which the wall that bounds the inlet channel has an inwardly directed lip which, together with the skirt portion, provides an anchor point for a meniscus that defines a fluidic seal for preventing fluid leakage during operation.

7. A micro-electromechanical fluid ejection device as claimed in claim 1, in which the beam assemblies are both substantially of titanium nitride.

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